

KEKB Accelerator Review Committee

23-25 Jan. 1997

BEAM INSTRUMENTATIONS

Beam Monitor Group

S.Hiramatsu

1. Beam Position Monitors (BPMs)
2. Synchrotron Radiation Monitors
 Beam size and profile
3. DCCTs
4. Others

1. Beam Position Monitor

- Electrostatic pickup with 4 buttons
- 452 BPMs/LER

Type	φ94	φ150	H150xV94	Others
Numbers	414	14	22	~2

- 452 BPMs/HER

Type	H104xV50	φ150	Others
Numbers	398	38	~16

- Pickup electrode; 12mmφ button
- Position resolution ; <10μm
- Measurable range; 10μm<|x,y|<10mm
10mA<|i_b|<2.6A
- Frontend electronics; superheterodyne
signal: 1GHz IF: 20kHz
ADC at 20kHz
spectral analysis by DSP
- Processing time; <250msec/button with 10μm
resolution (S/N>92dB) @<10mA
- Closed orbit measuring time; <1sec/4-buttons(programable)
- Prototype frontend processor; S/N~90dB in 0.25sec/button
(more 2dB?)
- One frontend processes 4 BPMs(2 for LER & 2 for HER) .
1st step: 226 frontends
- Signal test at AR;
direct signal: <0.1mA bunch current - measurable
spectrum analysis: S/N~92dB is expected at i_b=2.6mA .

- Narrow band coupling impedance ($\sigma_z=4\text{mm}$);

LER: $3.2\text{k}\Omega/400 \text{ BPM} (@7.6\text{GHz})$

HER: $4.7\text{k}\Omega/374 \text{ BPM} (@7.5\text{GHz}) [1 \text{ cut}]$

$2.3\text{k}\Omega/374 \text{ BPM} (@7.0\text{GHz}) [2 \text{ cut}]$

Z_{\max} for $\tau_E=23\text{msec}$ at $\alpha=1\times 10^{-4}$, $v_s=0.01$

$2.3\text{k}\Omega$ for LER, $12.5\text{k}\Omega$ for HER

2. Synchrotron Radiation Monitor

Optical lines

- a. Beam image (beam size)
 - b. Streak camera (Bunch monitor)
 - c. Double-slit interferometer (beam profile)
-
- Beam size measurement with **diffraction corrected** beam image.
 - diffraction limited optics
 - $\sigma_x(\text{LER/HER}) = 472/650\mu\text{m} \rightarrow 507/680\mu\text{m}$ (observed)
 - $\sigma_y(\text{LER/HER}) = 69/120\mu\text{m} \rightarrow 102/158\mu\text{m}$ (observed)
 - diffraction spreading: 30-40 μm → correction by point spread function
 - SR extraction mirrors;
 - Be-mirror mounted on Cu block
 - effective area: LER 10mmHx44mmV
HER 10mmHx50mmV
 - location: LER FUJI straight section (QR4/QR5)
HER OHO straight section (QR3/QR4)
 - Wavefront-correction mirrors will be employed to correct the wavefront distortion by thermal deformation of the extraction mirror.
 - Laser system for optics calibration will be installed.
 - Point spread function (diffraction) & mirror distortion will be measured.

- Mirror distortion monitor;
 - Shack-Hartmann sensor (laser+interferometer with micro-lens array)
 - sensitivity: $0.02\mu\text{m} \sim \lambda/30$ (surface distortion)
 - feedback to the wavefront correction mirror
- Beam profile measurement with **double-slit interferometer**.
 - $\lambda=300-700\text{nm}$
 - resolution; $\Delta\sigma < 1\mu\text{m}$
 - requirement; contrast of interference pattern $> 3\%$
 - intensity unbalance of 2 beams $< 1.5\%$
 - (feedback by beam shifter and PMs)

3.DCCTs

- KEK original DCCTs will be installed.

measurable range;	$10\mu\text{A} < i_b < 3\text{A}$
response;	DC-10kHz
drift;	$1-3\mu\text{A}/\text{deg}$
- The prototype DCCT was tested at the AR with 600mA beam current.

responce;	DC-500Hz
drift;	$5-8\mu\text{A}/\text{deg}$
accuracy;	$\sim 0.5\%$

*No problem in the DCCT itself but small problem of heating in the ceramic break of the beam chamber ($\sim 80\text{deg}$ @570mA).

4.Others

4-1 One-Turn BPM

20 one-turn BPMs are planned.

1-5 bunches will be selected by a fast analog SW.

Expected resolution; $50-70\mu\text{m}$ @ $i_b=0.1\text{mA}$ ($S/N \sim 60\text{dB}$)

Fundamental components were tested at AR.

Bunch selection by analog SW

Signal detection by I/Q demodulator

$S/N \sim 43\text{dB}$ @ $i_b=0.1\text{mA}$, single bunch

(more improvement required?)

4-2 BPM at IP

Specially designed BPMs will be installed in the QCS beam chamber (55mm ϕ inner diameter).

pickup; 4 buttons with 6mm ϕ diameter

feedthrough; SMA

4-3 Event Timing

Bunch detectors will be installed in the IR.

pickup; electrostatic pickup with wide and smooth response (same one as the bunch-by-bunch feedback signal detector)

locations; 2 in both sides of IR for each ring

4-4 Laser-Wire Monitor

Laser/beam timing was tested in the Tokyo Univ. linac at JAERI.

Collision experiment is under way.

electron beam; 17MeV, 150pC/pulse

beam size: 480 μm

laser; 790nm, 100fsec, 210mJ

spot size: 100 μm

timing jitter; $\sigma_t \sim 3.7\text{psec}$

4-5 Bunch Current Monitor

Beam current of every bunch is measured in the signal processing systems of bunch-by-bunch feedback.

tested in AR; synchronous det. at 1.5GHz
 error<5%(affected by synchrotron oscl.)
 reqired I/Q demod.

4-6 Tune Measurement

Transverse & vertical tune are measured in the signal processors of bunch-by-bunch feedback systems.

4-7 Wall Current Monitor

Each ring of LER and HER has a wall current monitor for bunch identification.

Design & fabrication will be in '97-'98.

4-8 Fast CT

Each ring of LER and HER has a fast CT for bunch current calibration.

Design & fabrication will be in '97-'98.

Heating problem of the ceramic break in the beam pipe should be solved.

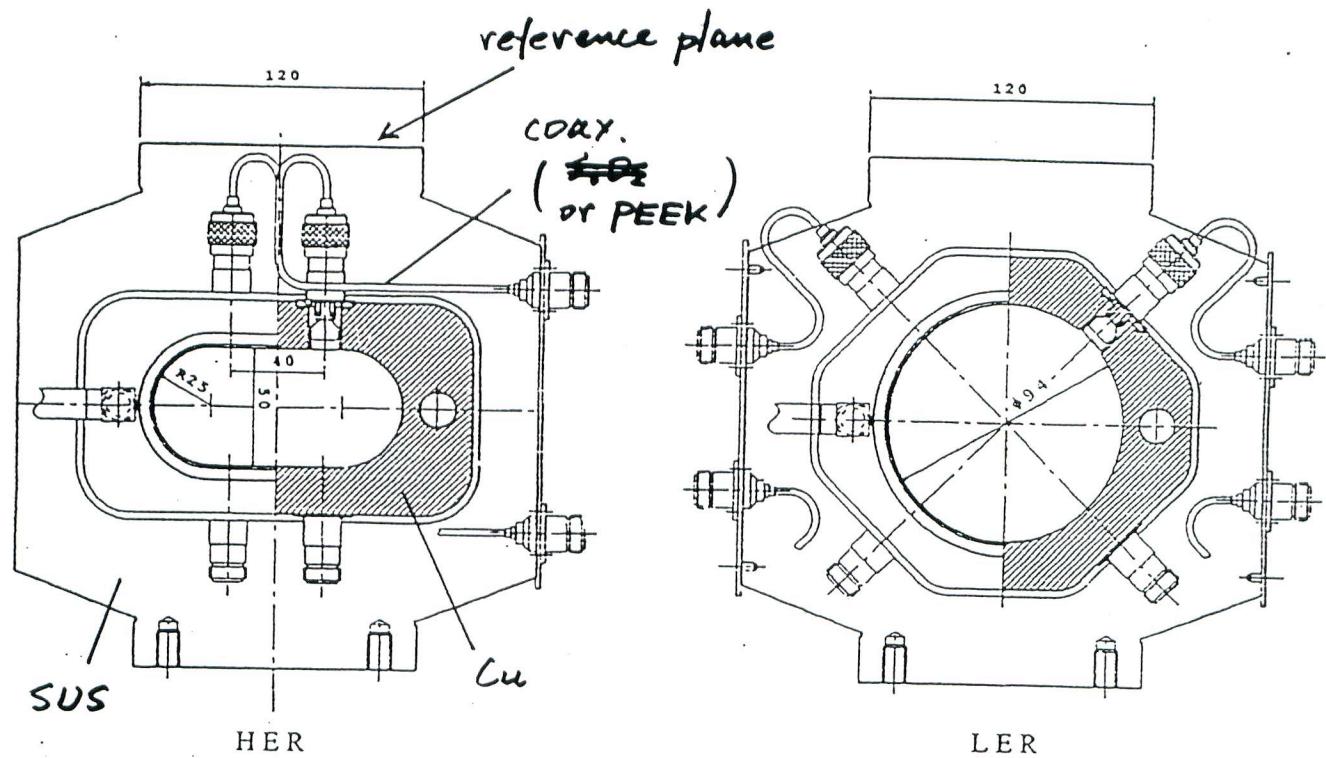
4-9 Screen Monitor

No plan for the screen monitors.

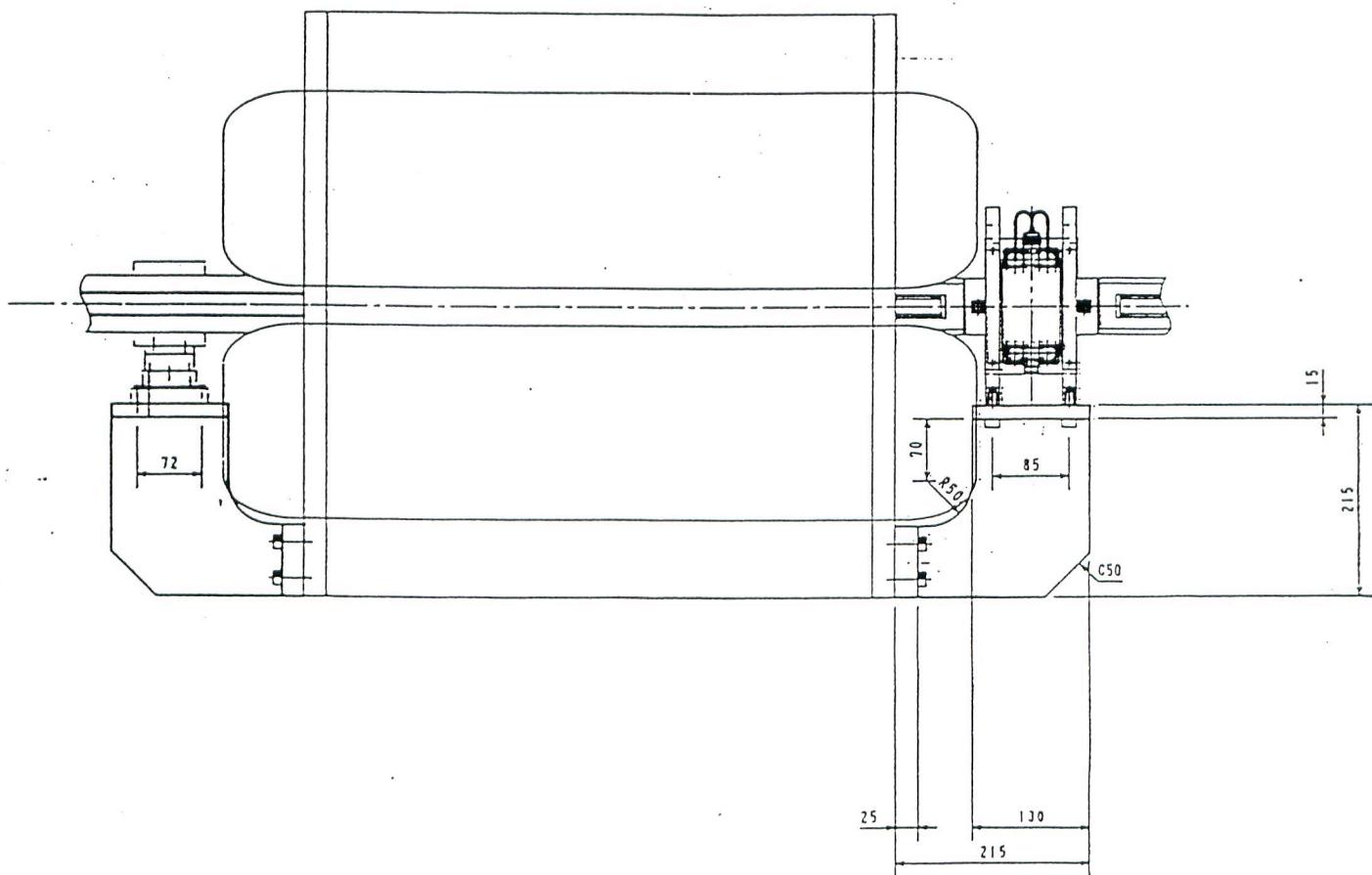
Direct signals from 452+452 BPM heads can be monitored instead of the screen monitors.

4-10 Beam Loss Monitor

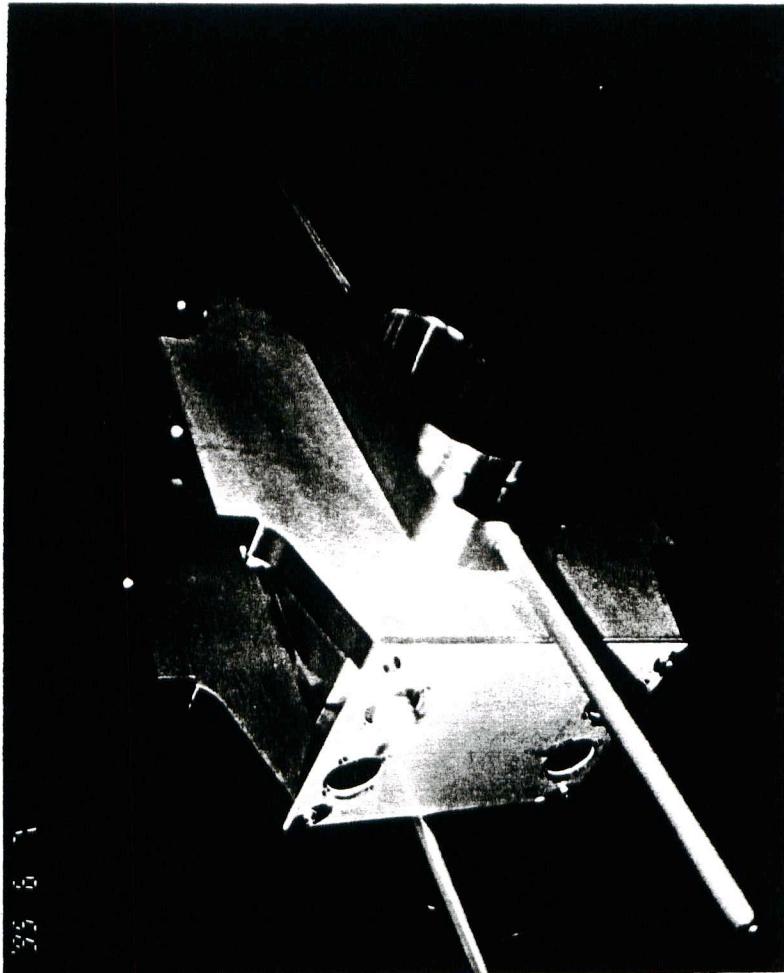
No plan for the beam loss monitors.



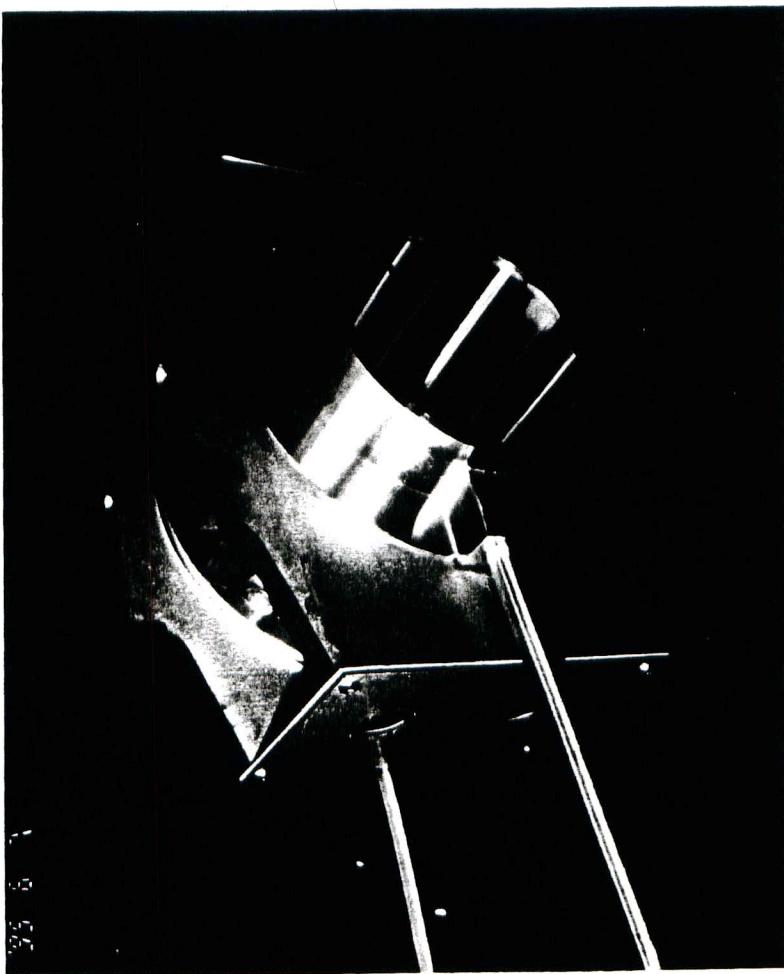
BPM block for the BF ring



BPM block for the HER

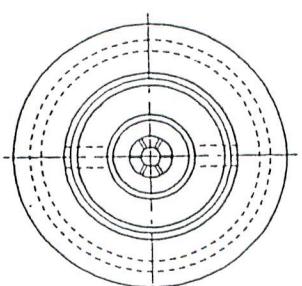
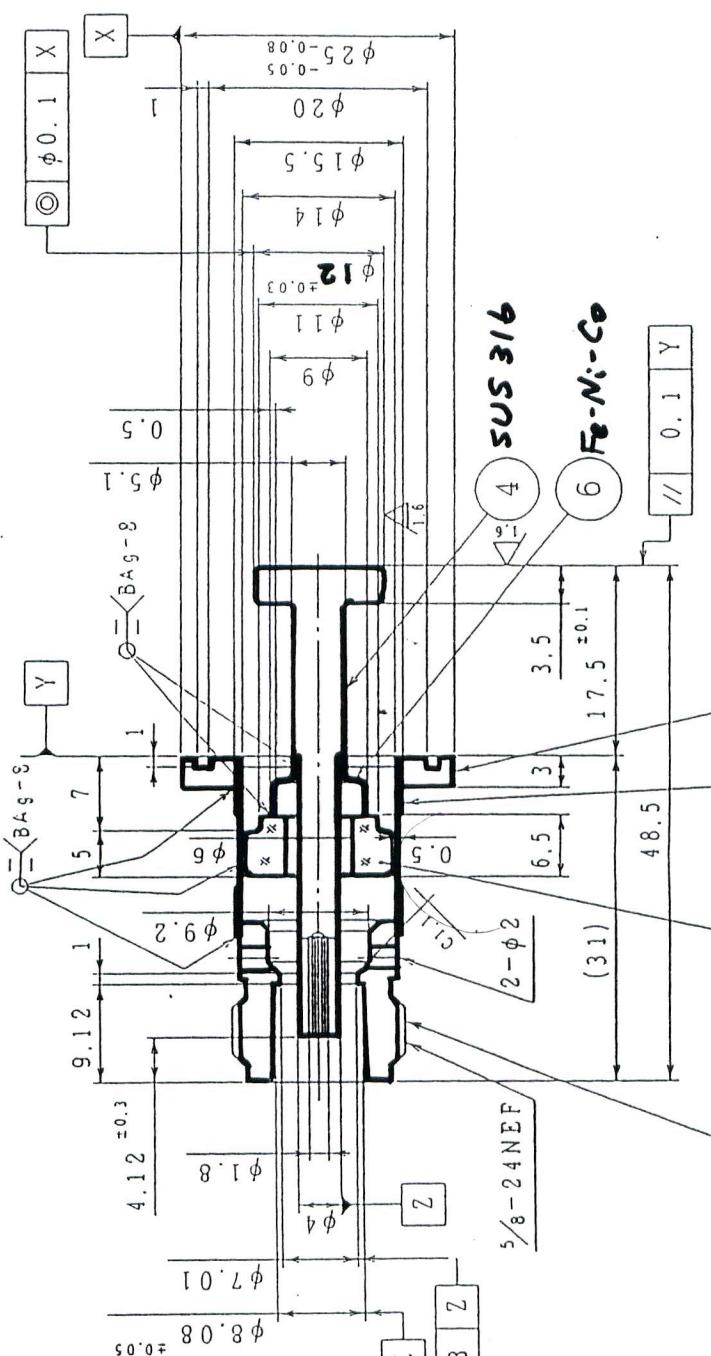


BPM block for the LER



BPM feedthrough / LER

記号	來	壓	年月日	訂正	密並	作番
						P43195



1. 気密性: 1×10^{-8} Torr · l / sec 以下 (於Hgリーグテイクタ-)

2. 施電圧: DC 1000V (於大気圧下1分間印加)

3. 絶縁抵抗: 1000MΩ以上 (於常温・常湿 50.0V印加)

仕様

SUS 304

ceramic Cu-Ni Cu
seal

1. 気密性: 1×10^{-8} Torr · l / sec 以下 (於Hgリーグテイクタ-)

2. 施電圧: DC 1000V (於大気圧下1分間印加)

3. 絶縁抵抗: 1000MΩ以上 (於常温・常湿 50.0V印加)

番号	部品名	材質	員数	備考	M.T		機付	機用	三脚法	製図尺度	原図縮尺
					入庫	発注					
①	端子	アルミニナセラミック	1	色焼:白							
②	パイプ	Cu-Ni	1	Niメッキ付							
③	フランジ	C1020	1	Niメッキ付							
④	ビン	SUS316	1	Niメッキ付							
⑤	スクリュー	SUS304	1	Niメッキ付							
⑥	L型フランジ	Fe-Ni-Co	1	Niメッキ付							

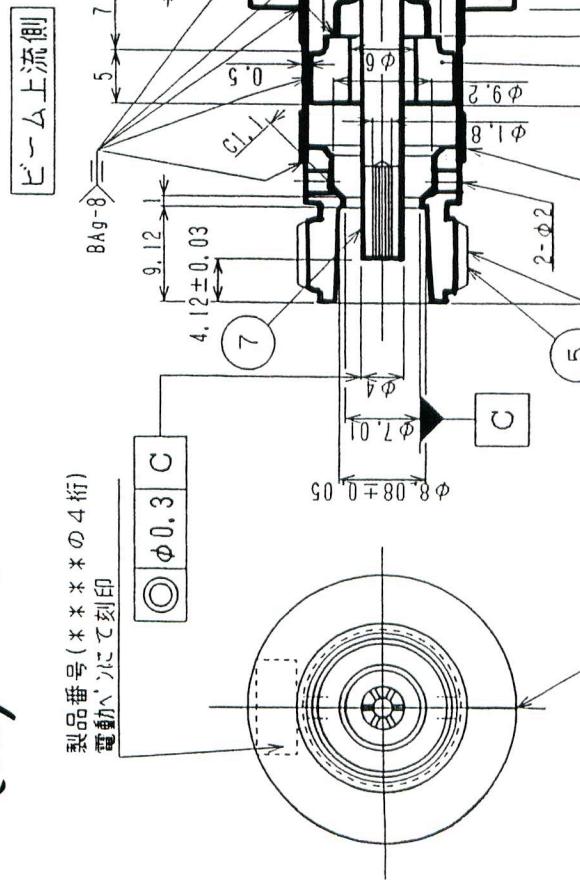
番号	部品名	品番	部品番	部品名	G T コード	検査料コード	材 料	村 村	寸 直	基 材	仕上	原図縮尺
①	端子											
②	パイプ											
③	フランジ											
④	ビン											
⑤	スクリュー											
⑥	L型フランジ											

NL-102-700

日立原町
電子工業

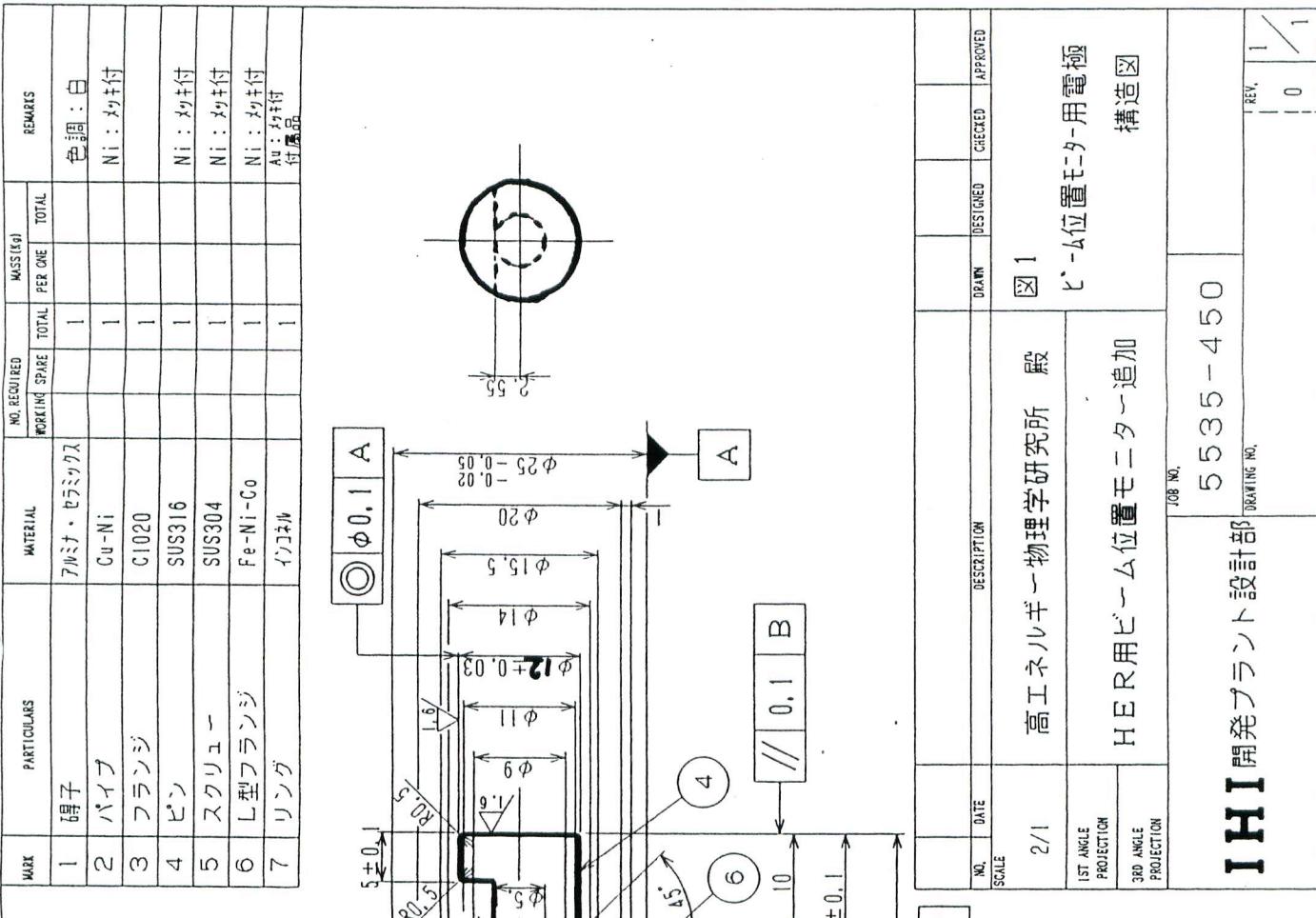
BPM feedthrough / HER
(asymmetric structure)

製品番号(＊＊＊＊の4行)
電動ベンにて刻印



著者
備

ケカチ線は、③フランジの中心を通り、かつ中心電極(④ヒビ)上の面Dに対して垂直にひくものとします。



1
四

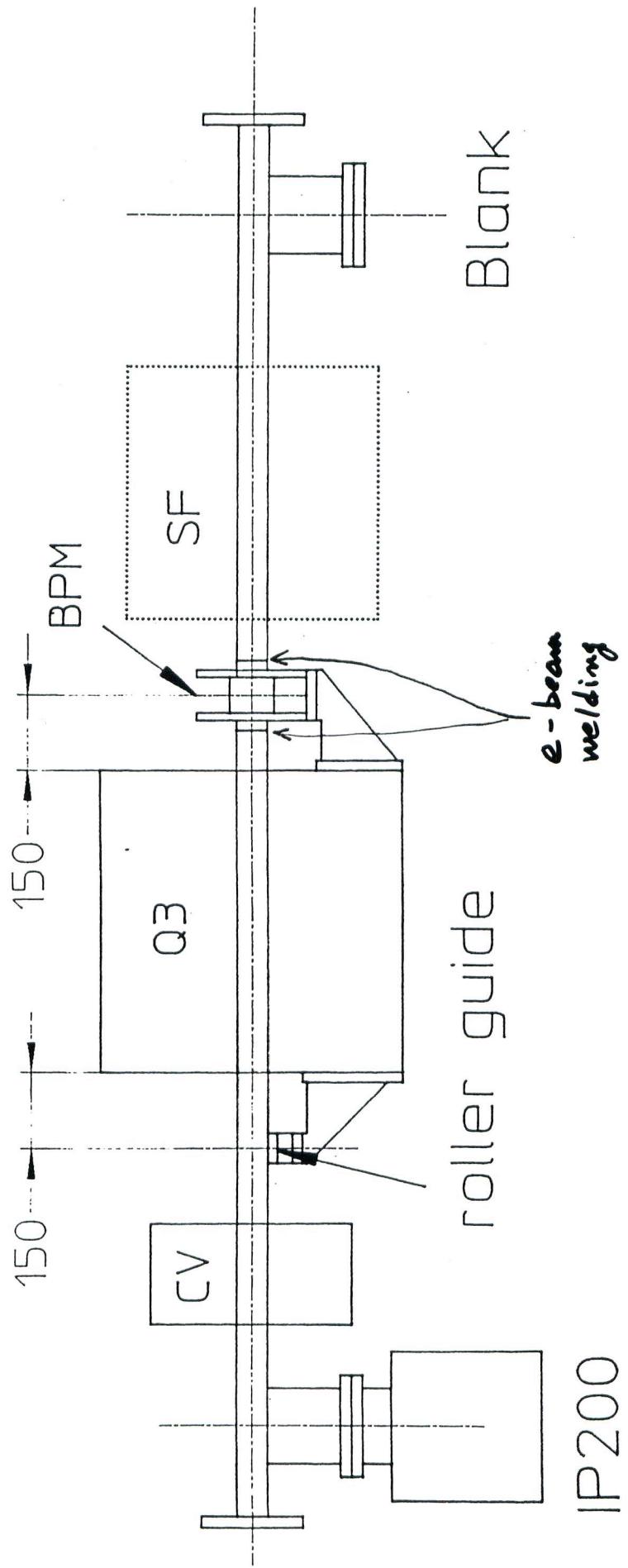
HE R用ビーム位置モニター追加構造図

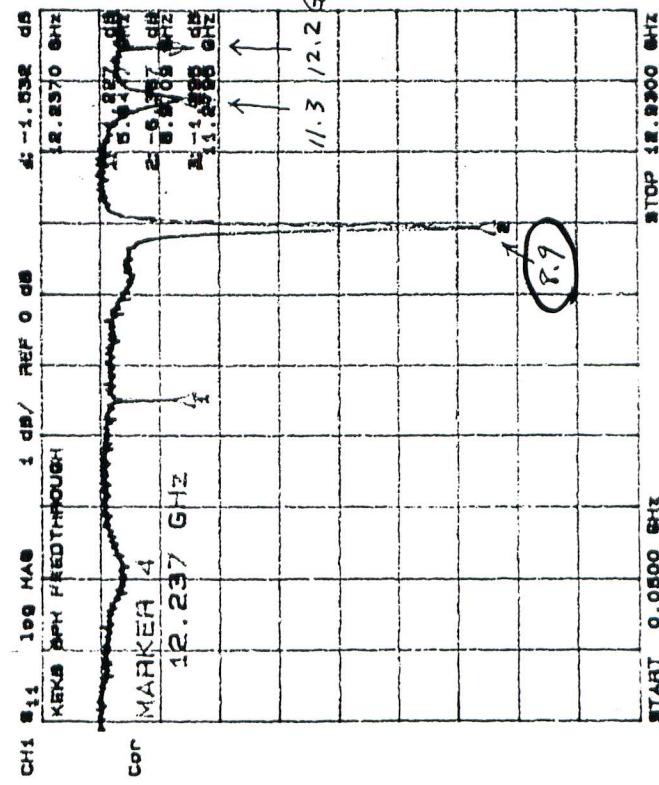
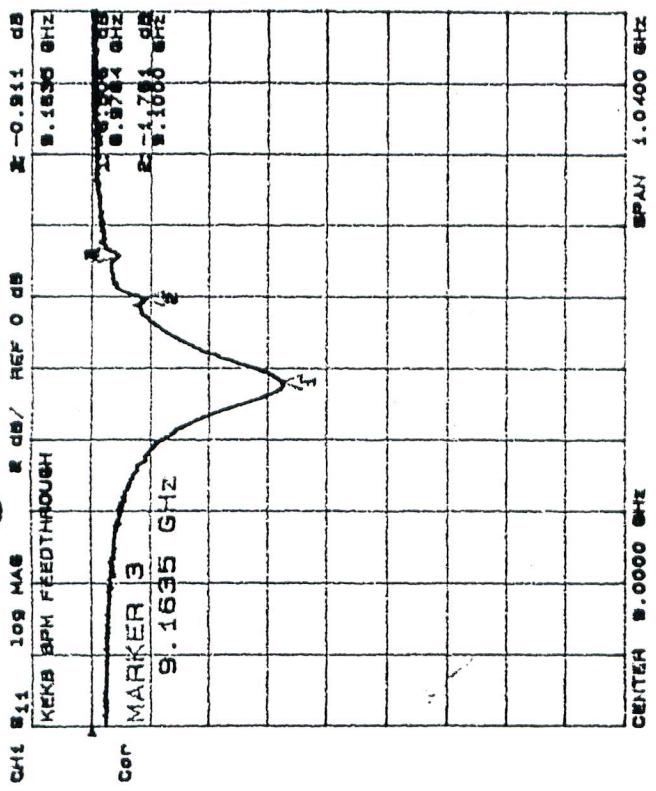
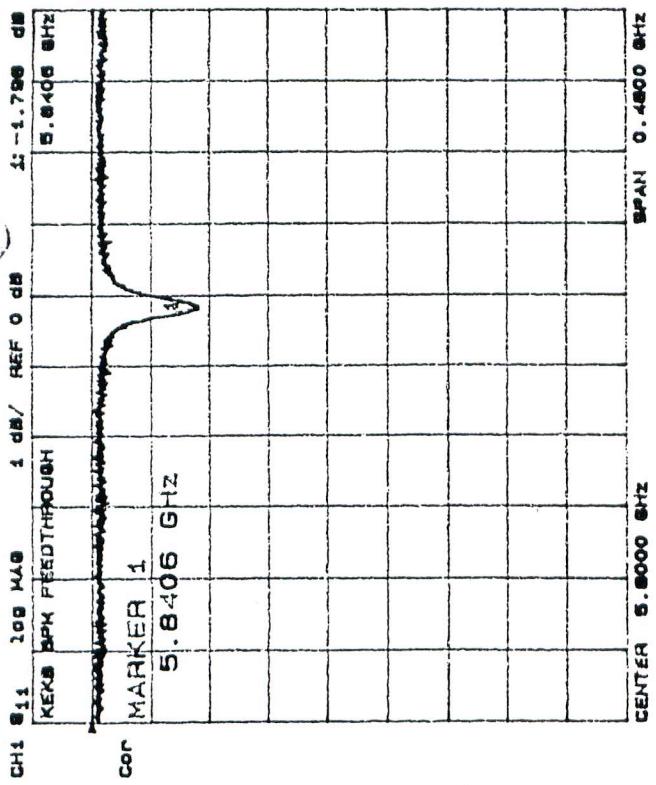
5535-450

Volume 110,

1 / 1
0

Ishikawajima-Harima Heavy Industries Co., Ltd.





BPM feedthrough S_{11}
(symmetric electrode)

1/1.8 , 1/2.5

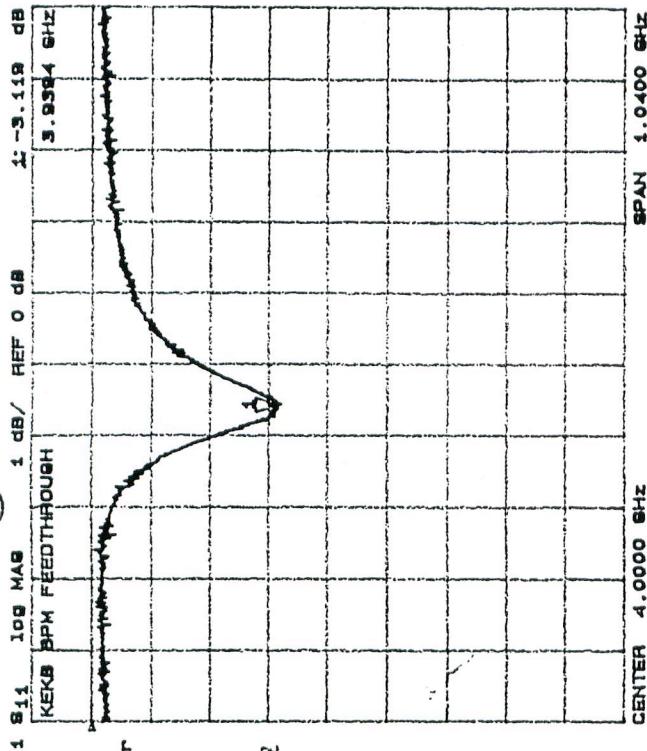
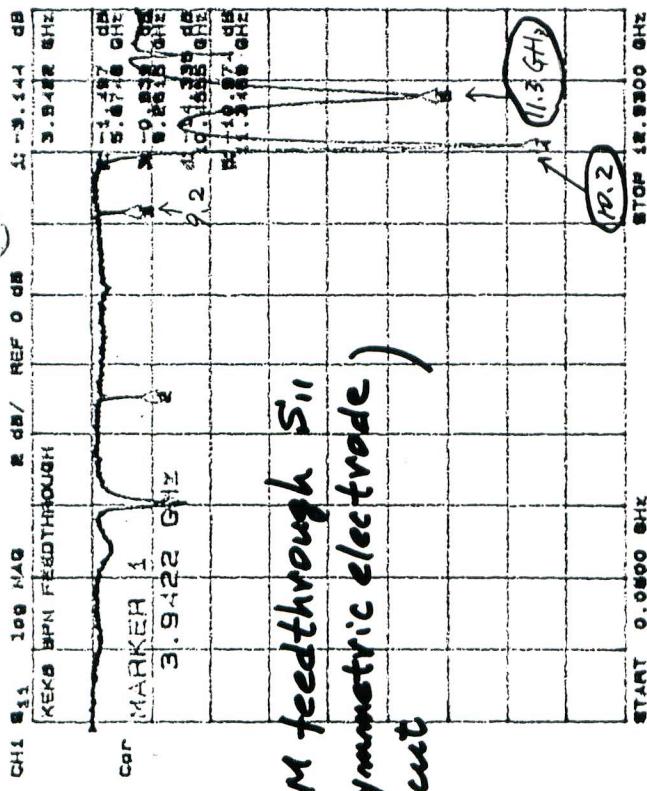
A⁻三測定

1996.12.12

3.962

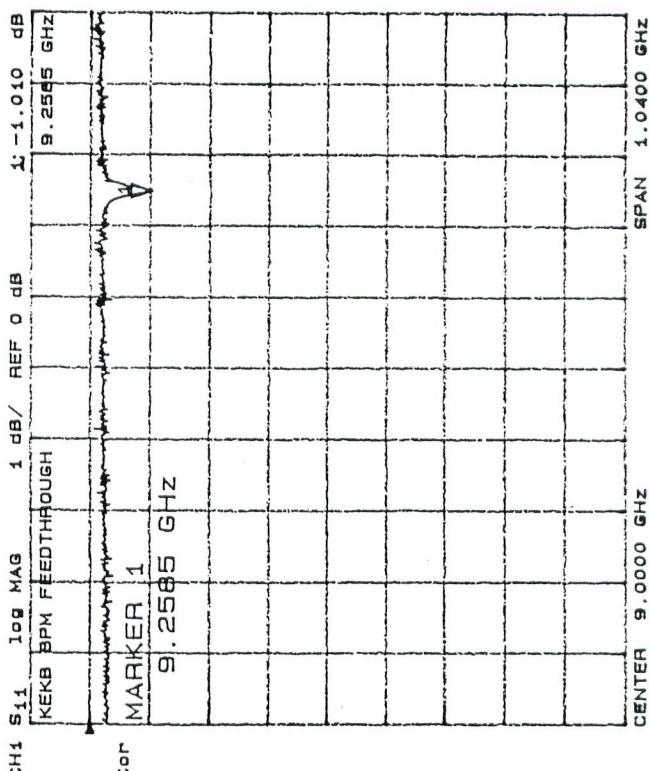
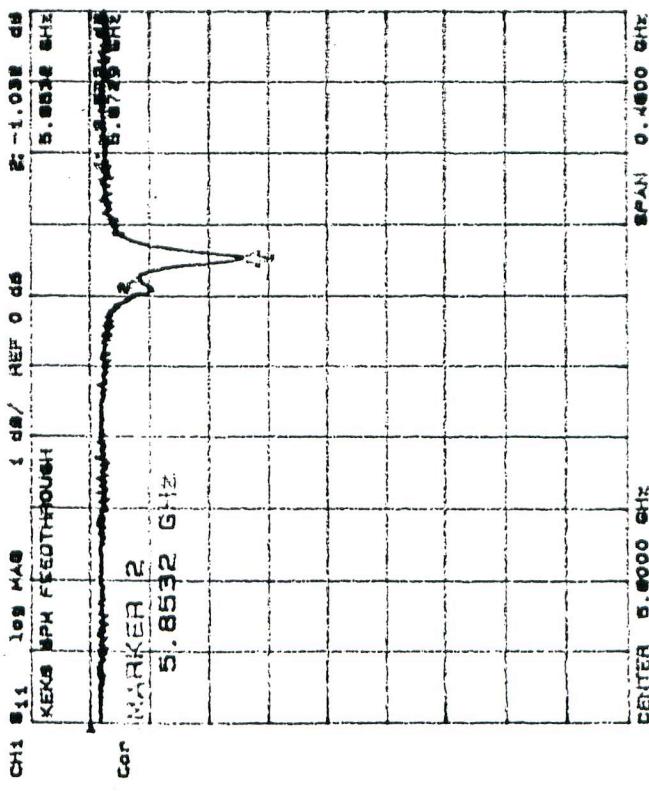
x7 3.56
x8 4.068

1996.12.12



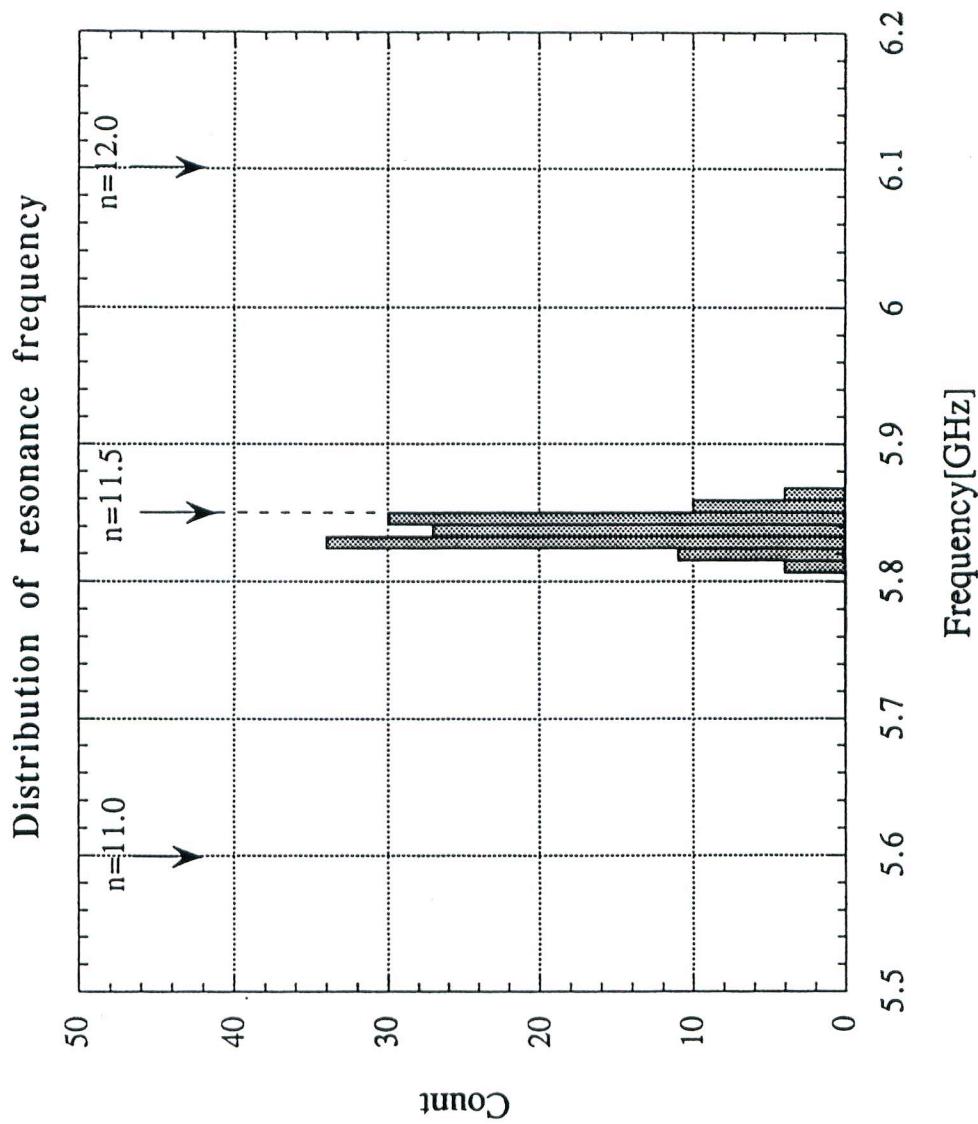
HER

600



BPM feedthrough :
(symmetric electrode)

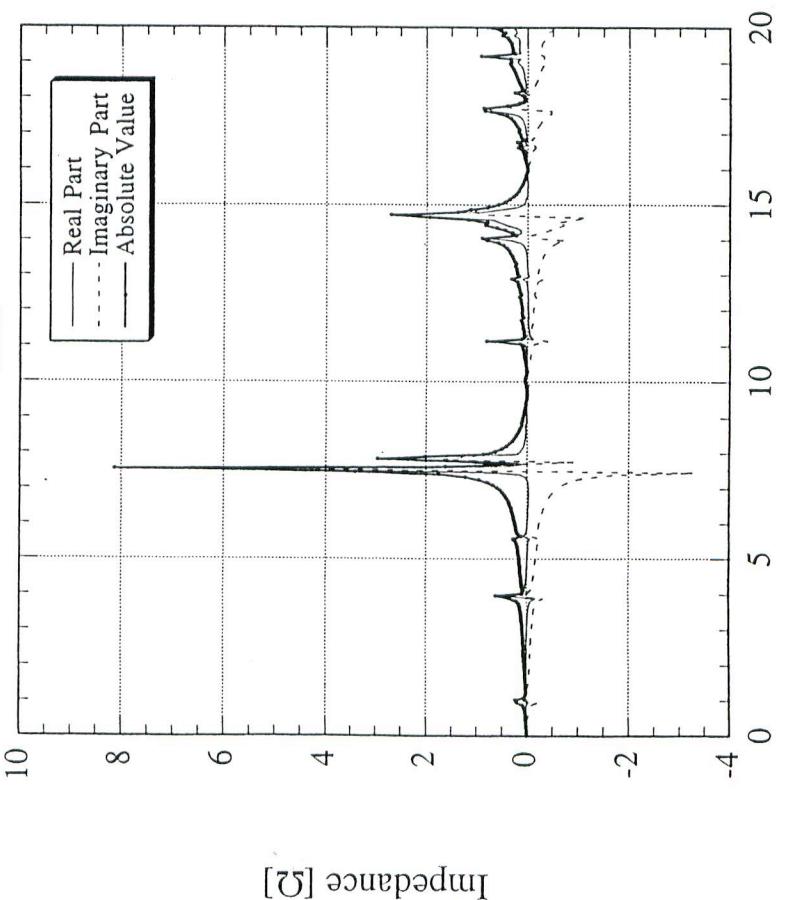
Resonance freq. in S_{11}



MAFIA

96. 6. 3

Longitudinal Impedance of KEKB BPM
(symmetric, $t_{button} = 5\text{mm}$)

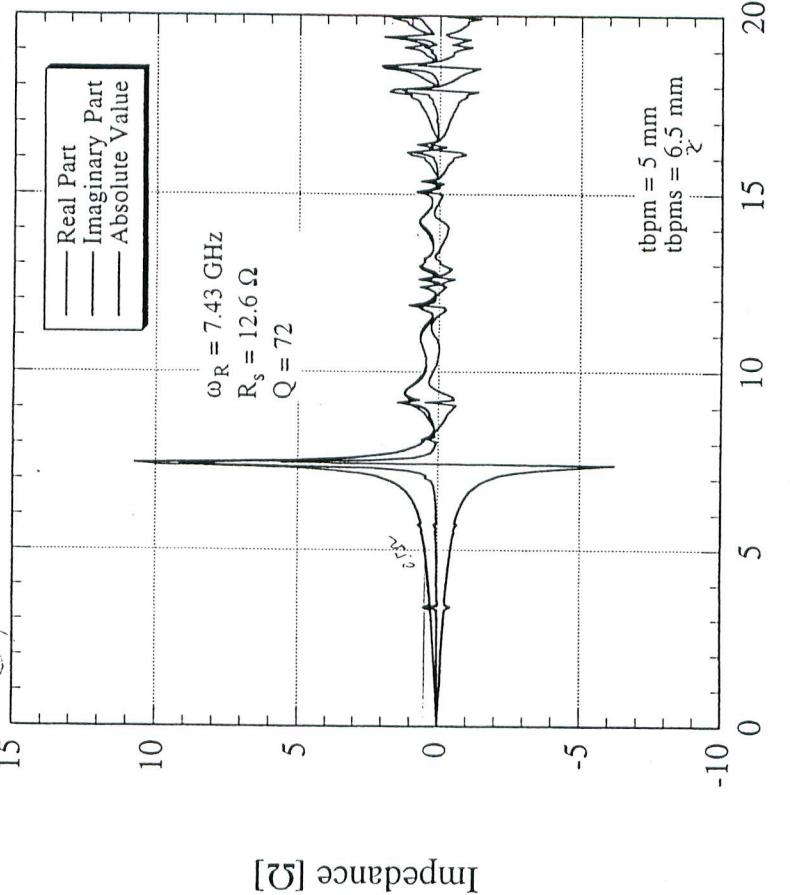


Frequency [GHz]

LER

Y - 2

Longitudinal Impedance of KEKB BPM
(1-cut asymmetric button, modified mesh)



Frequency [GHz]

HER

BPM Mapping Data

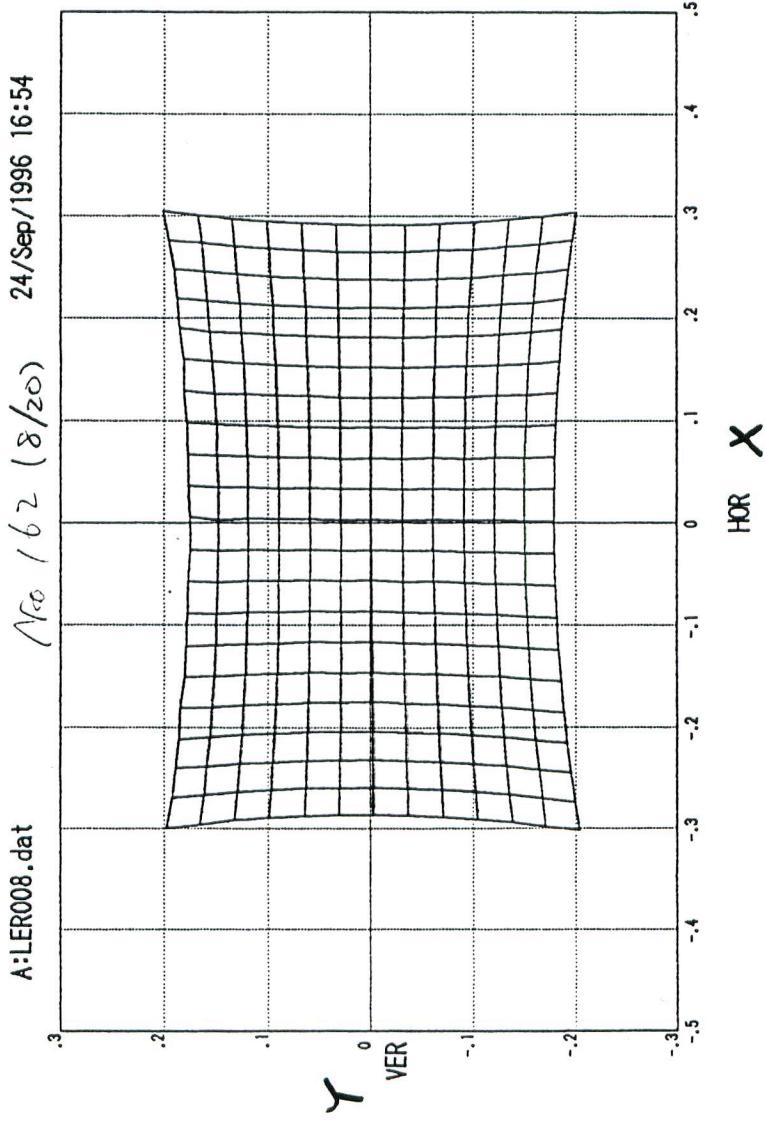
LER (94mmφ)

$$\begin{pmatrix} -10 \text{ mm} \leq x \leq 10 \text{ mm} \\ -6 \text{ mm} \leq y \leq 6 \text{ mm} \end{pmatrix}$$

H₀ = 109.75 H₁ = 219.82

$$X = \frac{(A+D)-(B+C)}{A+B+C+D}$$

$$Y = \frac{(A+B)-(C+D)}{A+B+C+D}$$

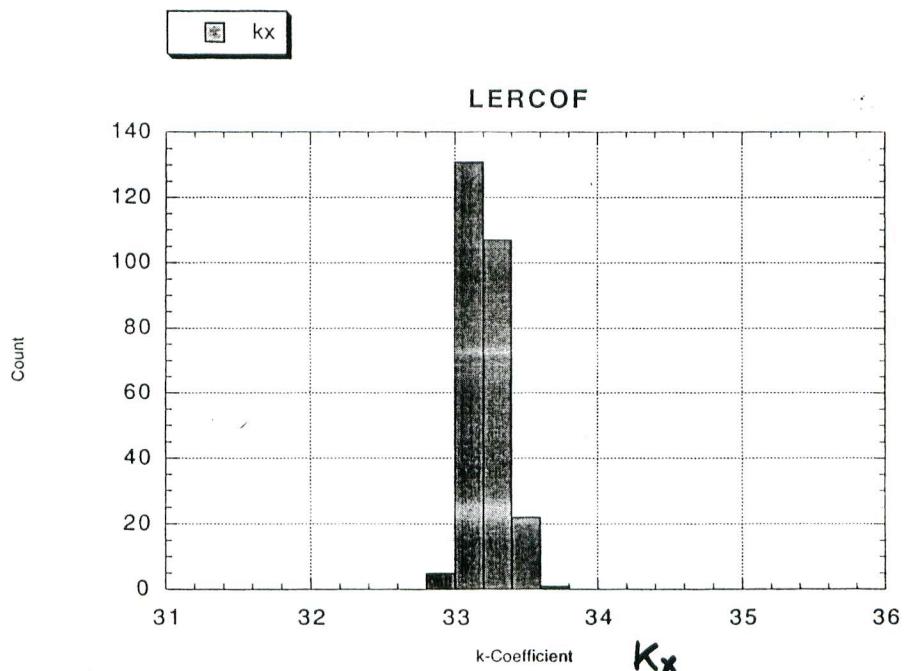


Origin (x0,y0) = (-0.111, 0.036)mm Kx= 33.05 , Ky= 33.02

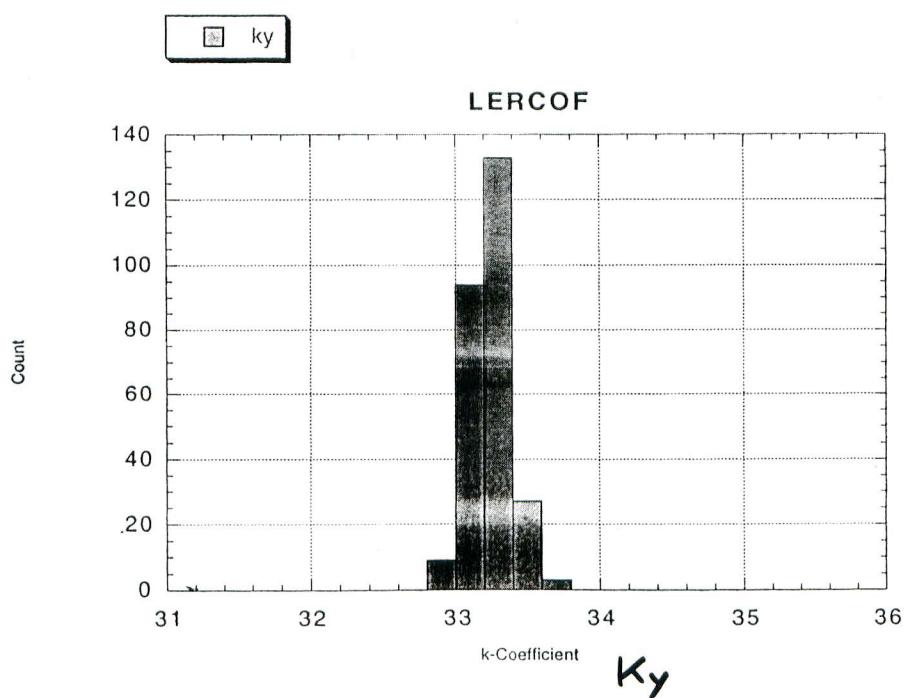
$$\begin{aligned} f(h,v) &= \begin{pmatrix} h \\ v \end{pmatrix} \\ f_x &= \begin{cases} -0.111 \\ 0.036 \end{cases} \quad \begin{cases} 33.047 \\ -0.176 \end{cases} \quad \begin{cases} h \\ v \end{cases} \\ f_y &= \begin{cases} 0.131 \\ 0.112 \end{cases} \quad \begin{cases} 0.251 \\ 0.023 \end{cases} \quad \begin{cases} v \\ 0.300 \\ 0.217 \\ 0.385 \end{cases} \quad \begin{cases} hh \\ hv \\ vv \\ hhv \\ hhh \\ 18.906 \\ 0.217 \\ 0.385 \\ 0.374 \end{cases} \quad \begin{cases} 100 \\ 620 \\ 43.077 \\ 44.777 \end{cases} \quad \begin{cases} hv \\ vv \\ hhv \\ hhh \\ 1.100 \\ 23.557 \end{cases} \\ &= \begin{cases} 0.111 \\ -0.176 \end{cases} \quad \begin{cases} 33.047 \\ -0.176 \end{cases} \quad \begin{cases} h \\ v \end{cases} \\ &= \begin{cases} 0.131 \\ 0.112 \end{cases} \quad \begin{cases} 0.251 \\ 0.023 \end{cases} \quad \begin{cases} v \\ 0.300 \\ 0.217 \\ 0.385 \end{cases} \quad \begin{cases} hh \\ hv \\ vv \\ hhv \\ hhh \\ 18.906 \\ 0.217 \\ 0.385 \\ 0.374 \end{cases} \quad \begin{cases} 100 \\ 620 \\ 43.077 \\ 44.777 \end{cases} \quad \begin{cases} hv \\ vv \\ hhv \\ hhh \\ 1.100 \\ 23.557 \end{cases} \end{aligned}$$

Standard error.....XE=(0.012)mm, YE=(0.009)mm

Distribution of K_x and K_y

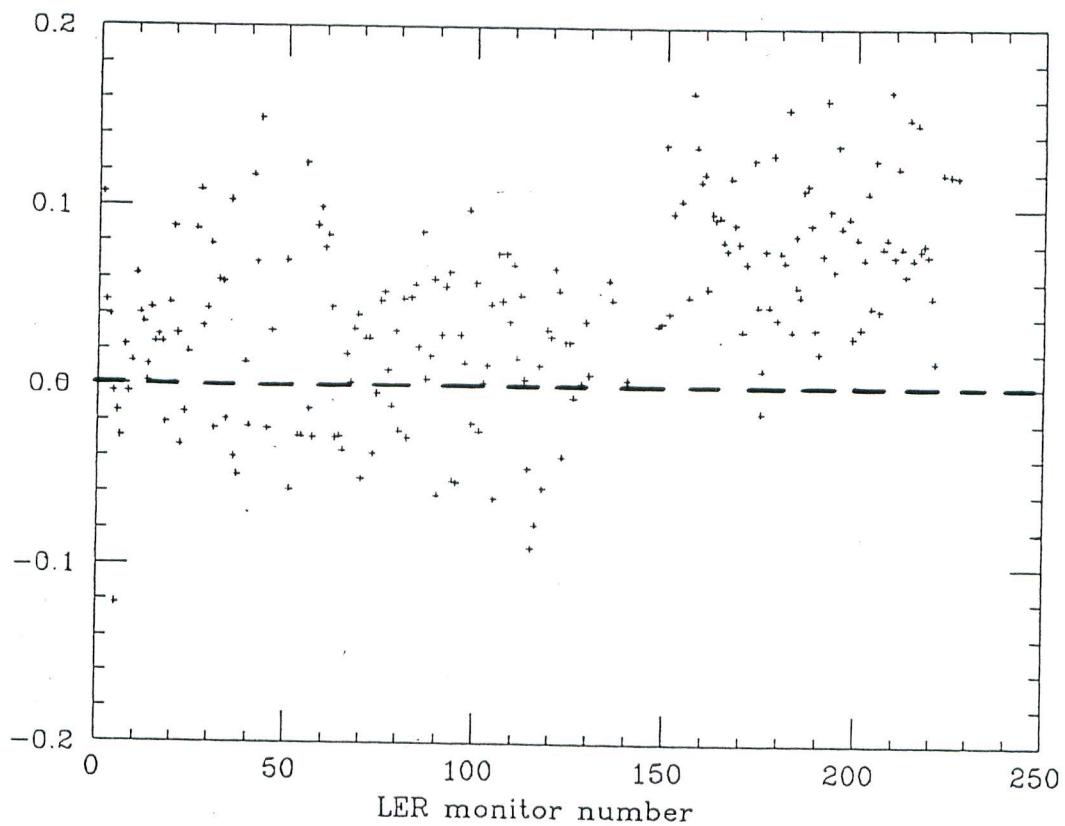


$$\left\{ \begin{array}{l} x = K_x X \\ y = K_y Y \\ (x, y \approx 0) \end{array} \right.$$

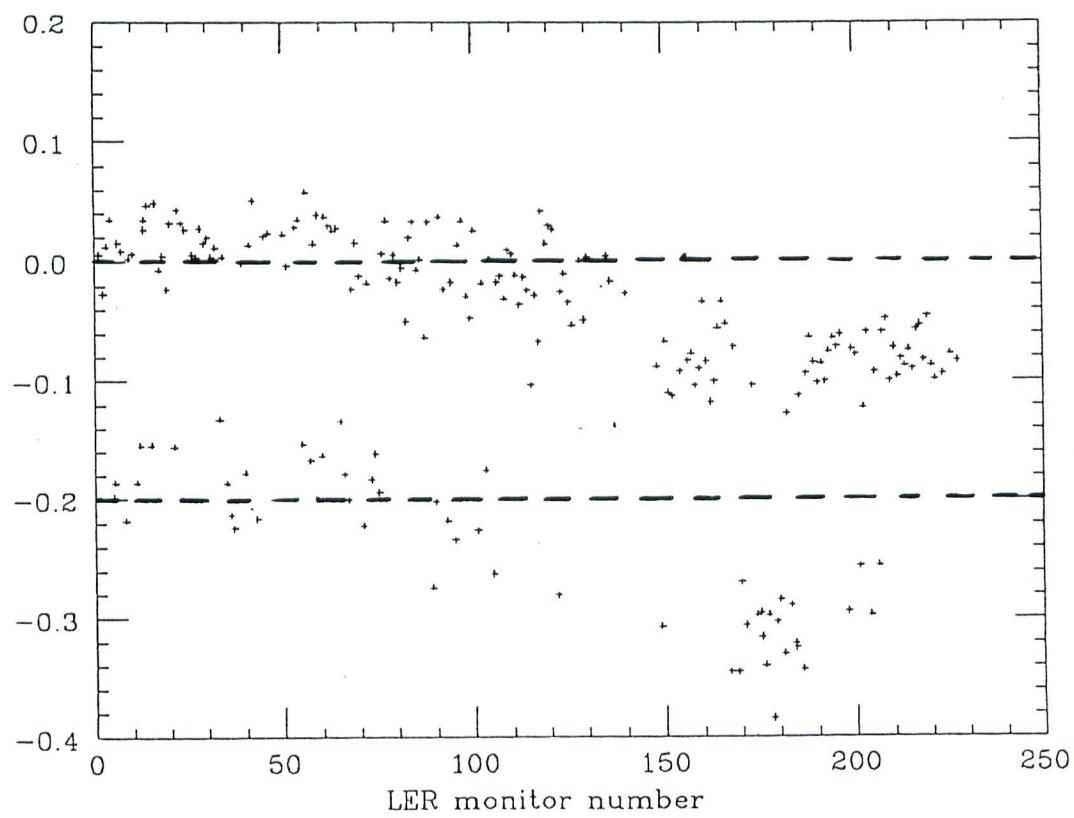


Analysis of Mapping Data by Least Squares Method

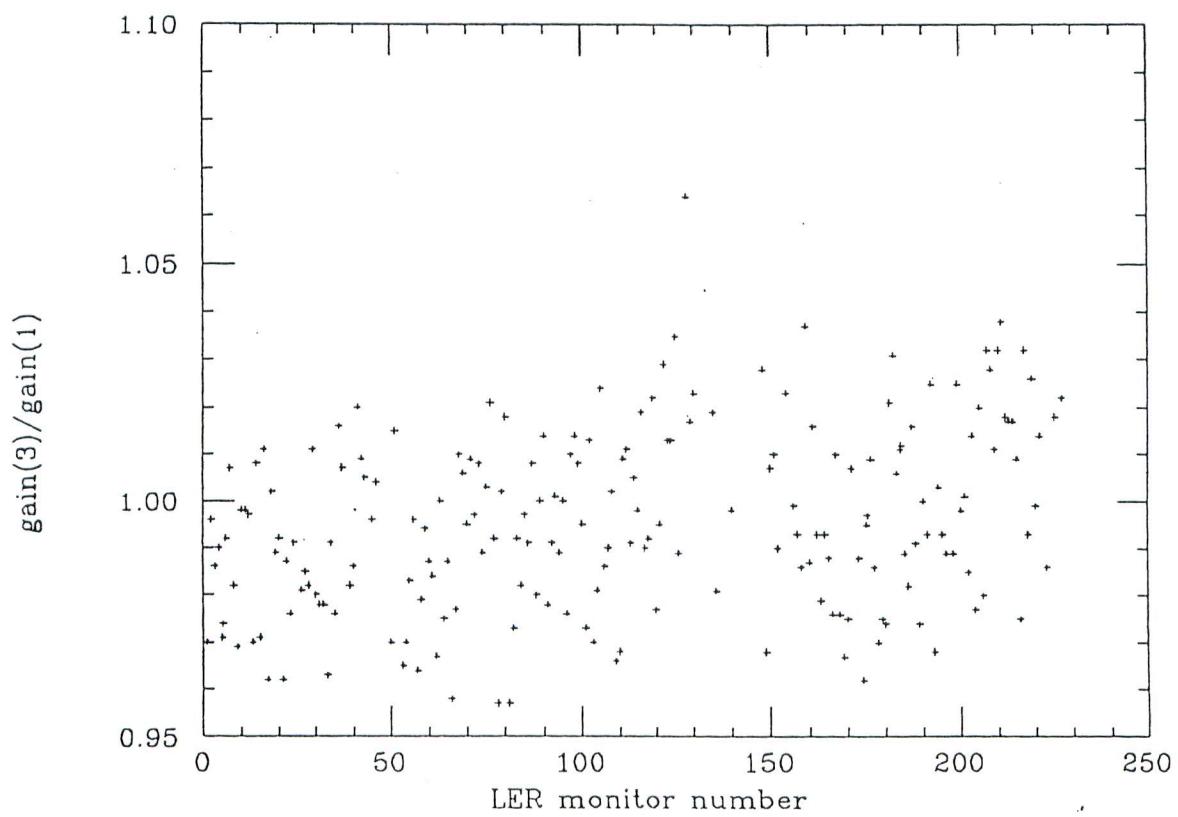
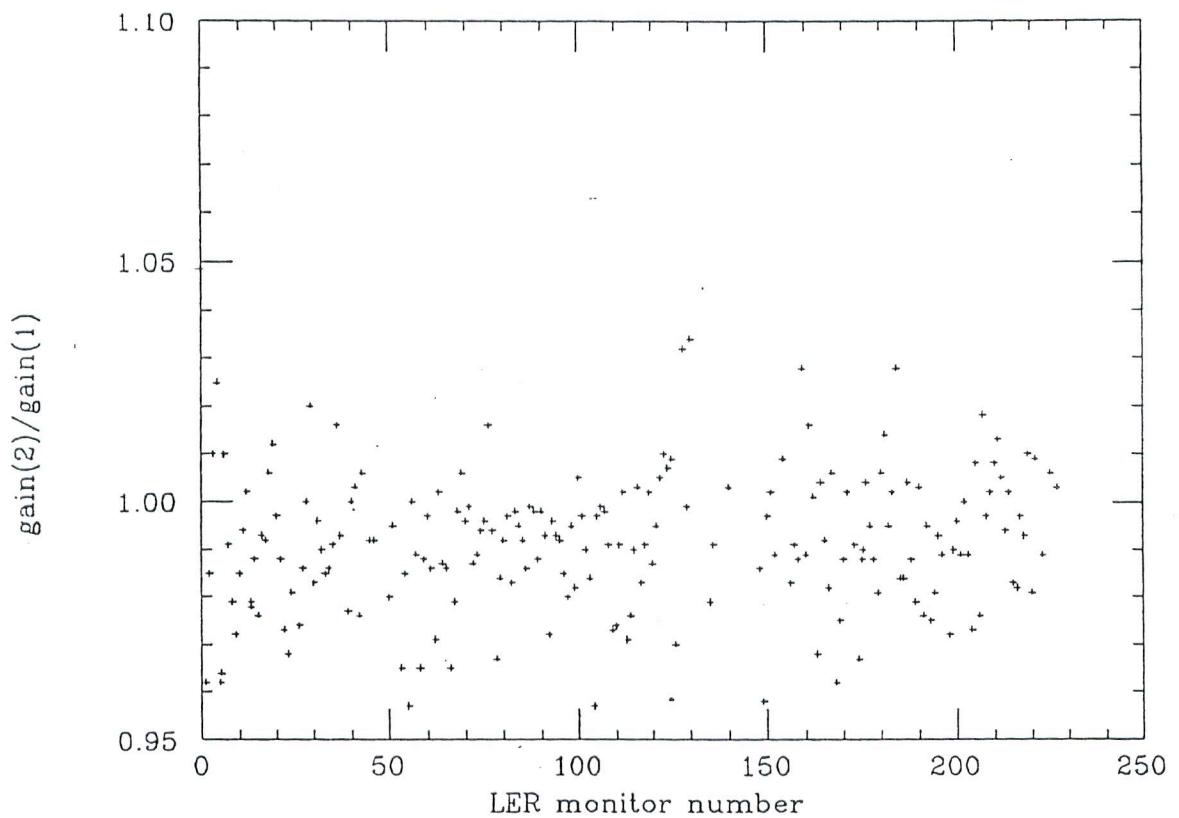
Horizontal center displacement(mm)

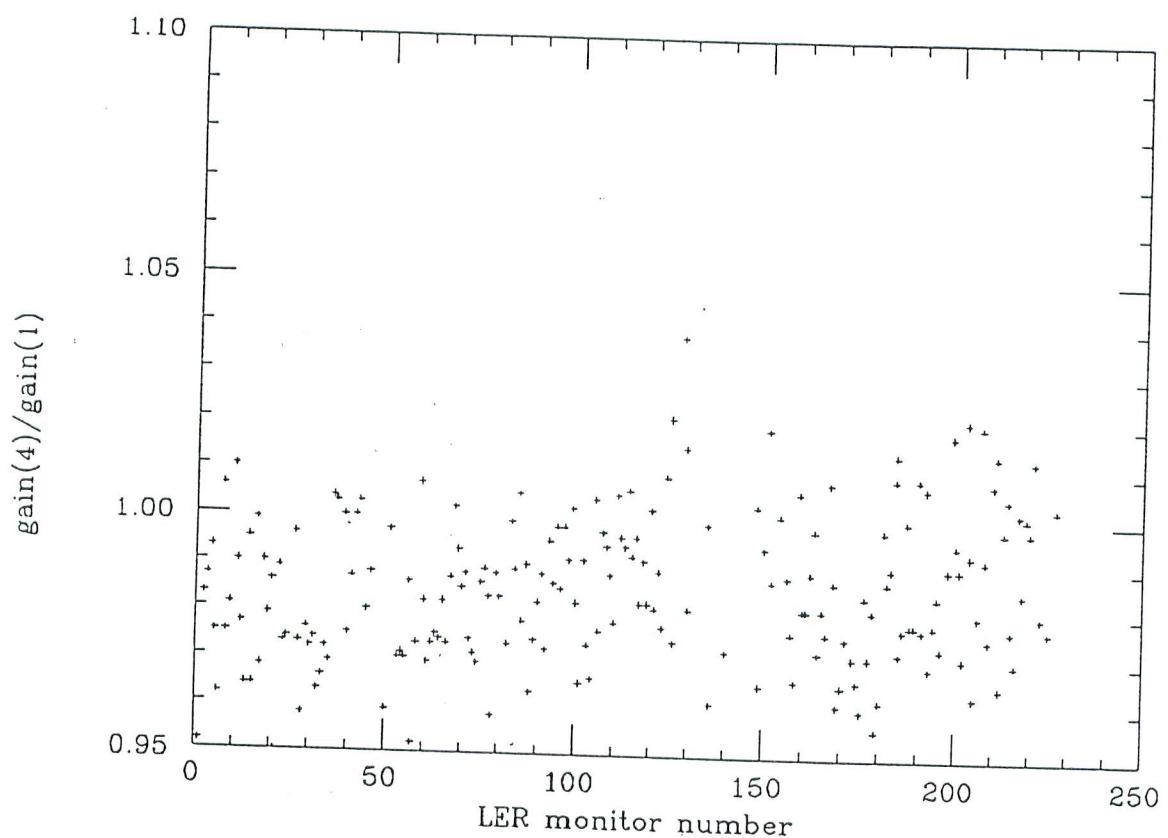


Vertical center displacement(mm)



Pickup Gain Balance





BPM Signal at AR

Tek

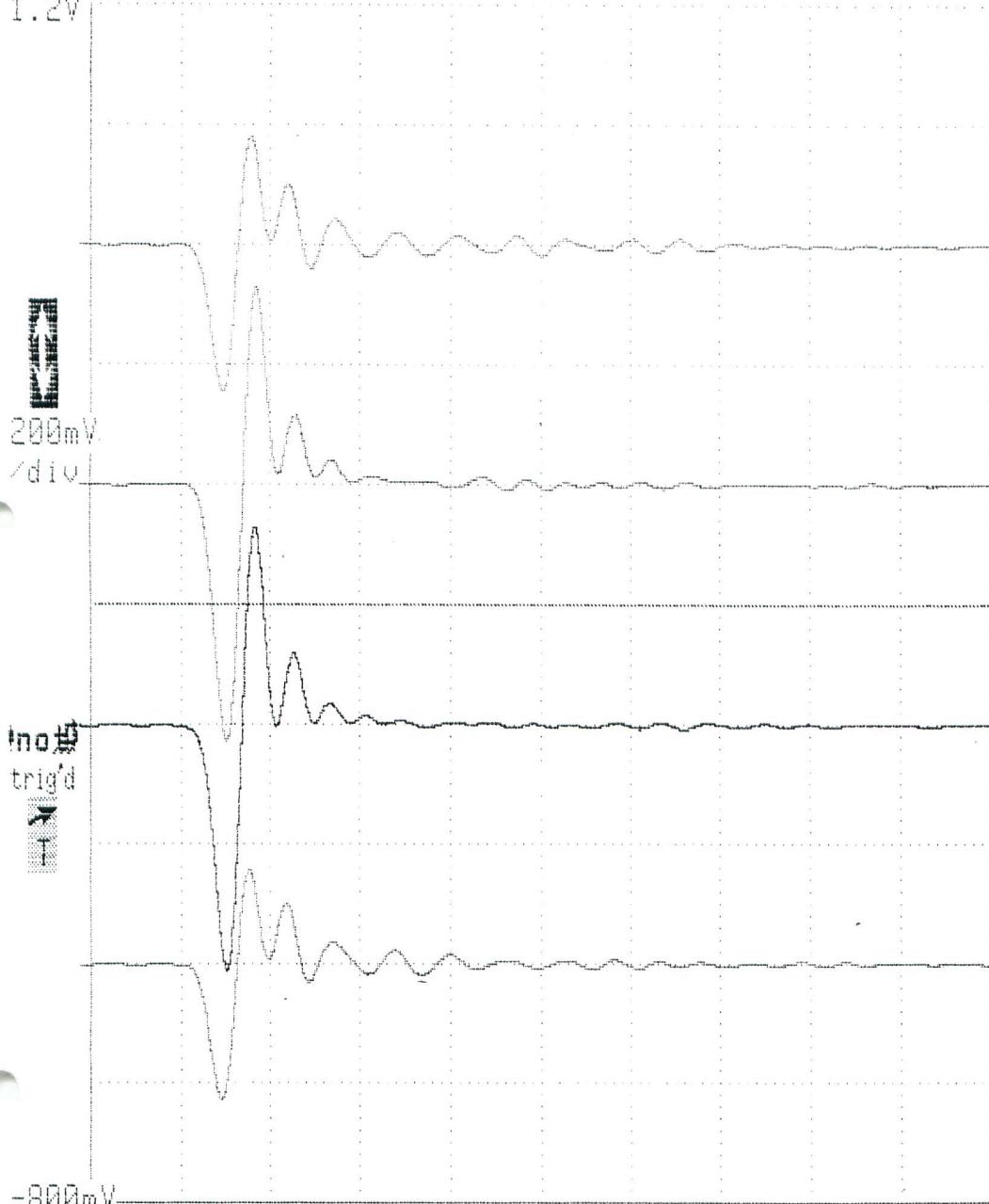


Cursors

FFTmag

Def Tra

1.2V



19.1 mV

≥ 6dB

313ps/sec

2.99 cm

A ST022

B ST023

C ST024

D ST025

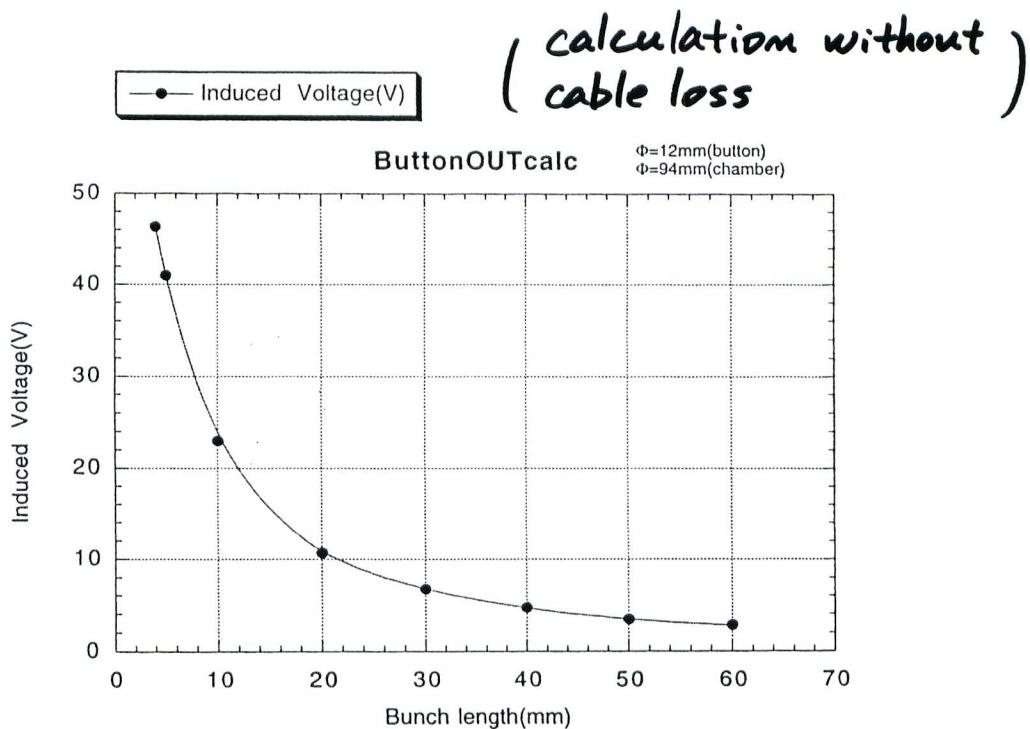
1.253μs

ins/div

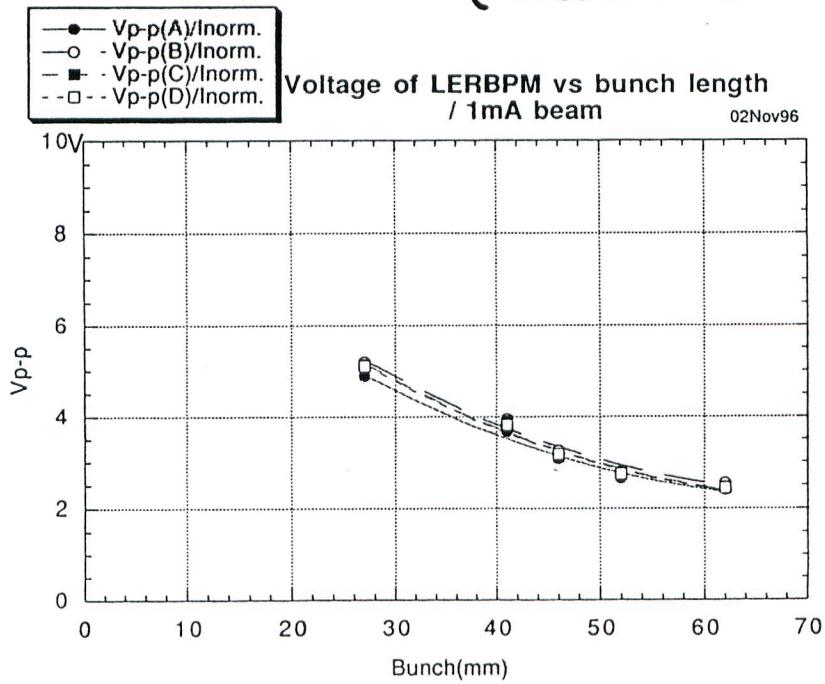
1.263μs

Store Trace	Recall Trace	Clear Trace	Delete Trace	Vert Mag: Tra 200mV/div
				Vert Pos: Tra 200mV
Store Setting	Recall Setting	Sequence Settings Off	Delete Setting	Remove/CirChan Trace 3 Sel ST024 Calcd Tra

Peak voltage of bunch signal (V_{pp})

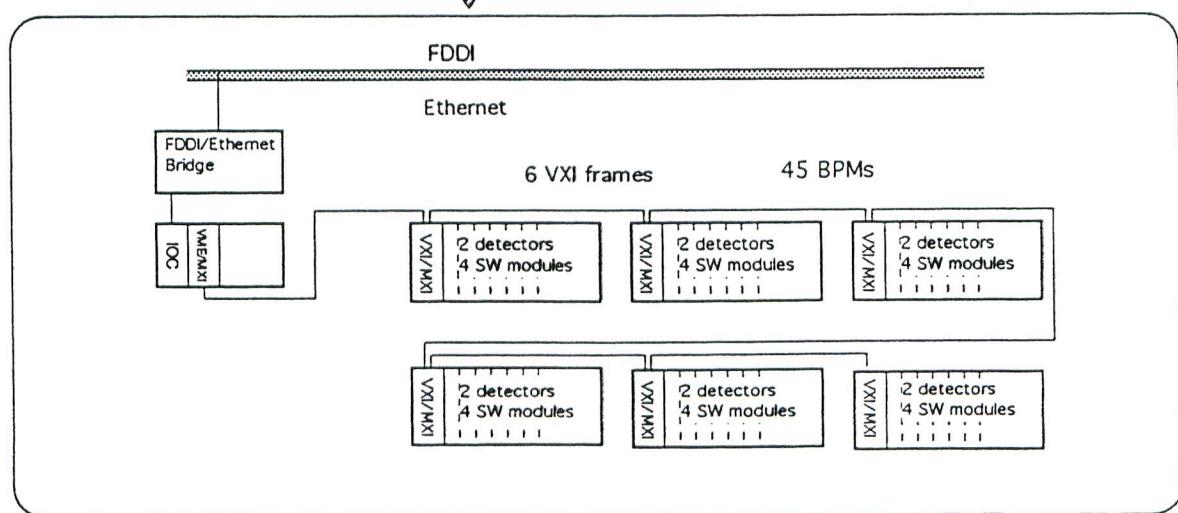
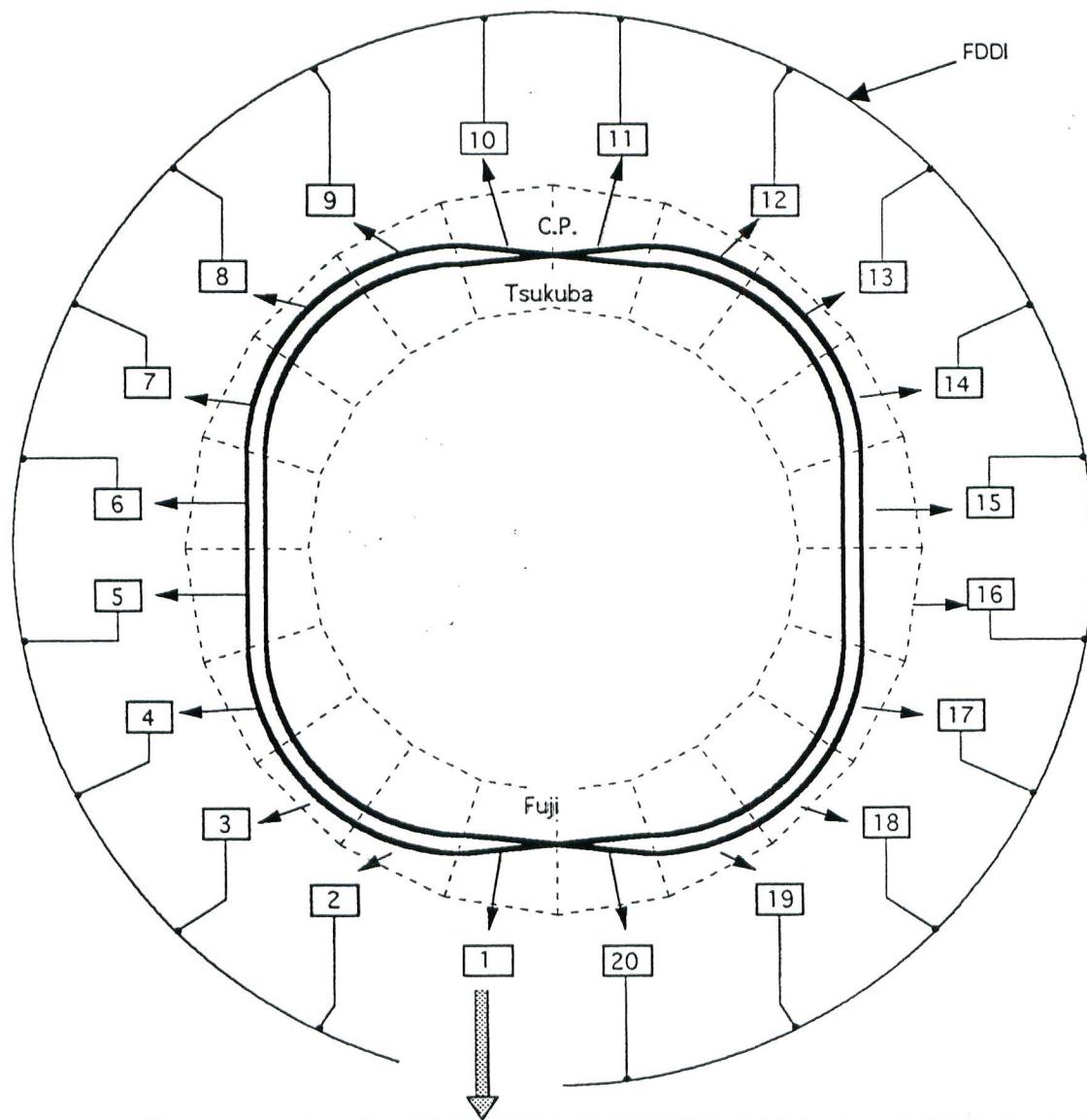


(measured at AR)

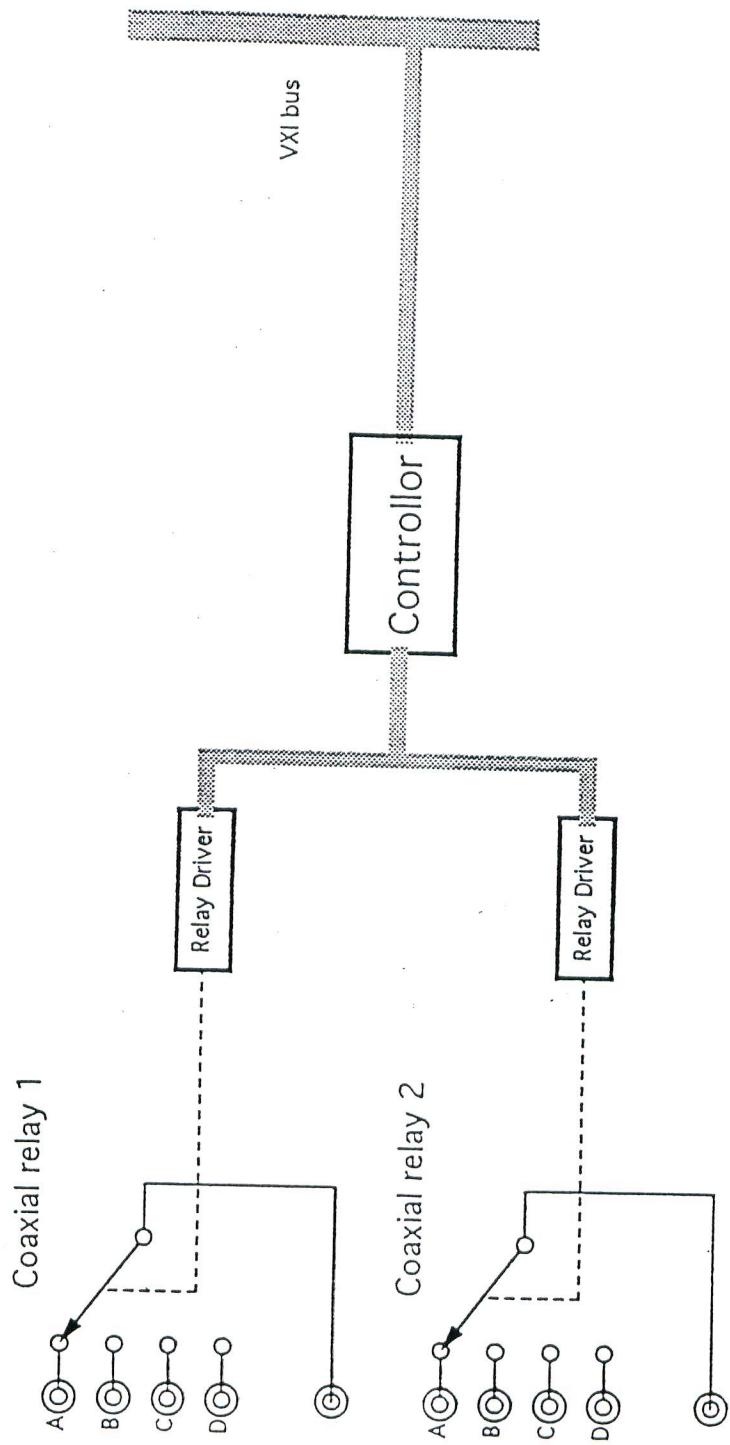


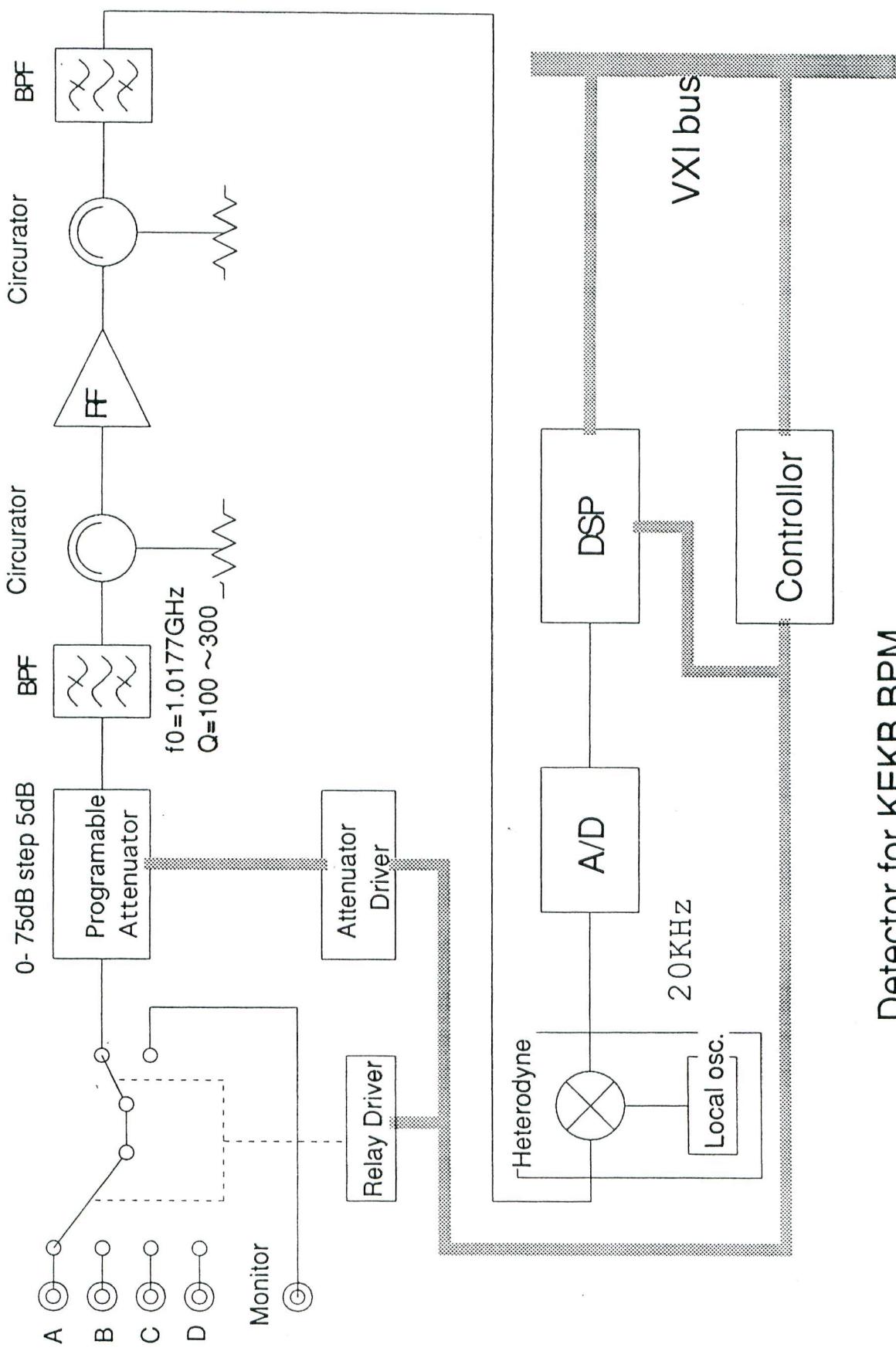
-12dBm @ 1.17GHz for $i_b = 570\text{mA}$

→ KEKB: -44dBm @ 1GHz for $i_b = 10\text{mA}$, Cable = 200m
 expected



Beam Position Monitor System for B-Factory
240 Detector circuits

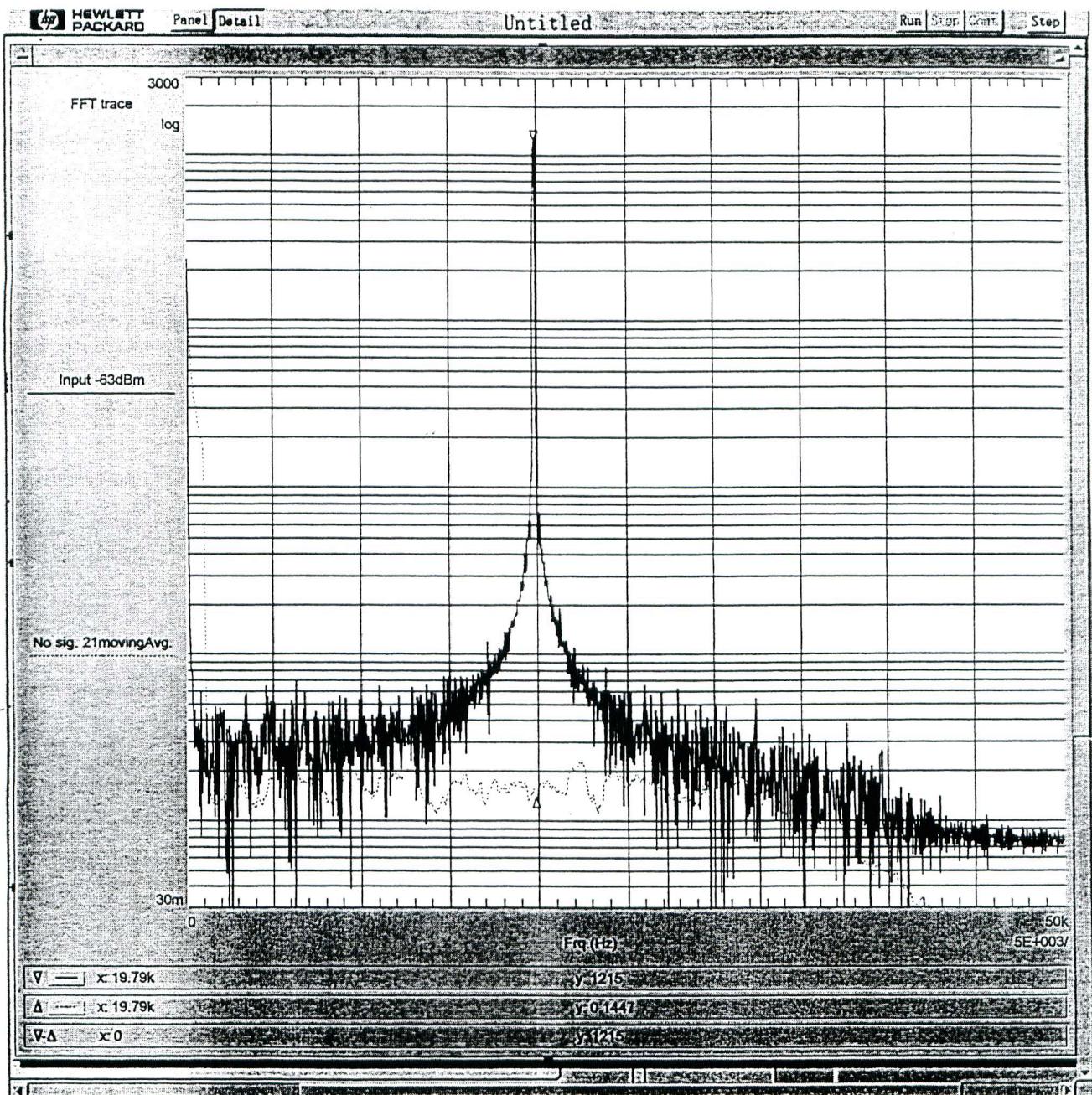




Detector for KEKB BPM

S/N Check of BPM Frontend

Tue 10/Dec/1996 17:08:46 PST



FFT 2048 points

av. 1

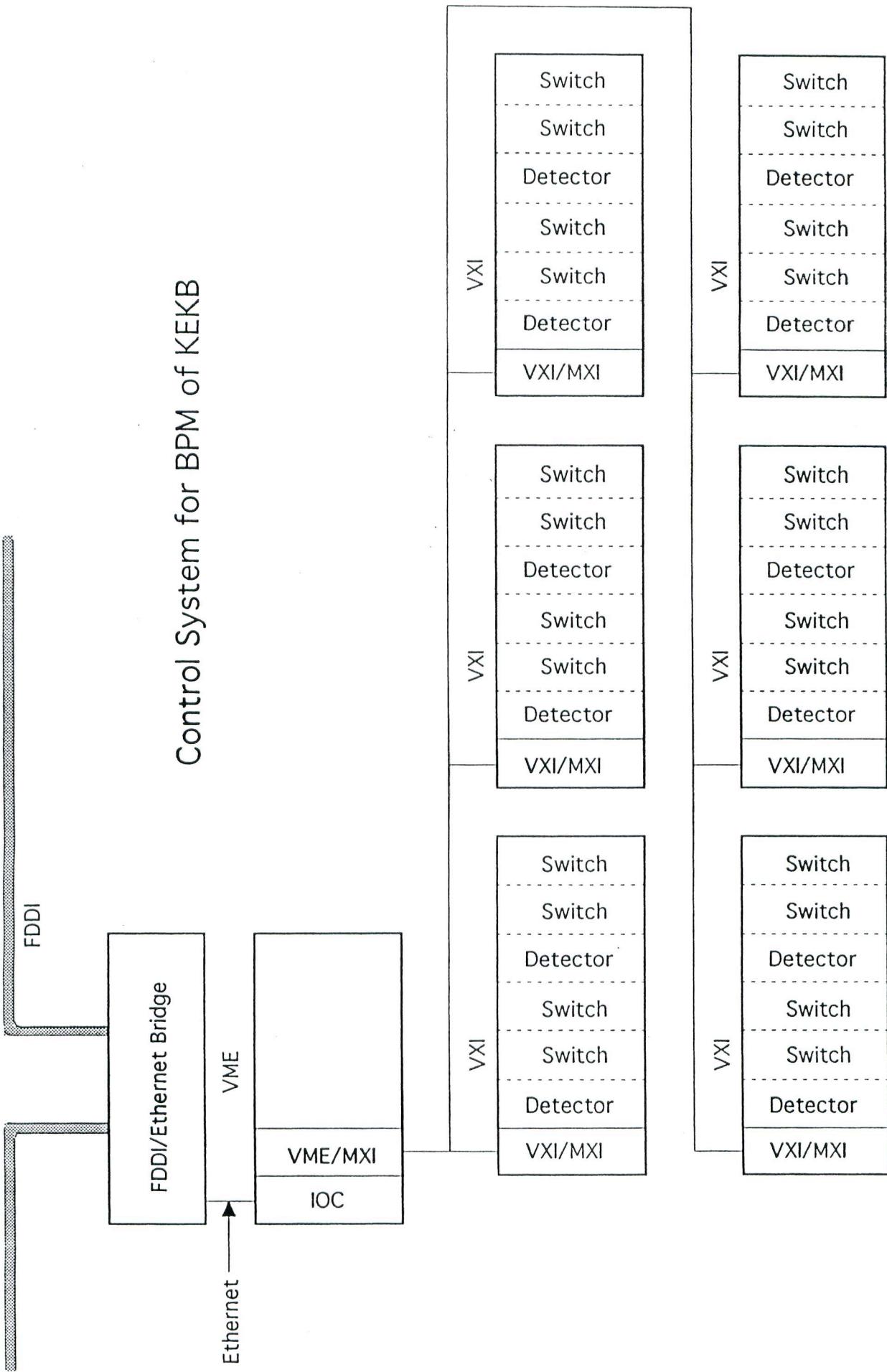
processing time ~40ms



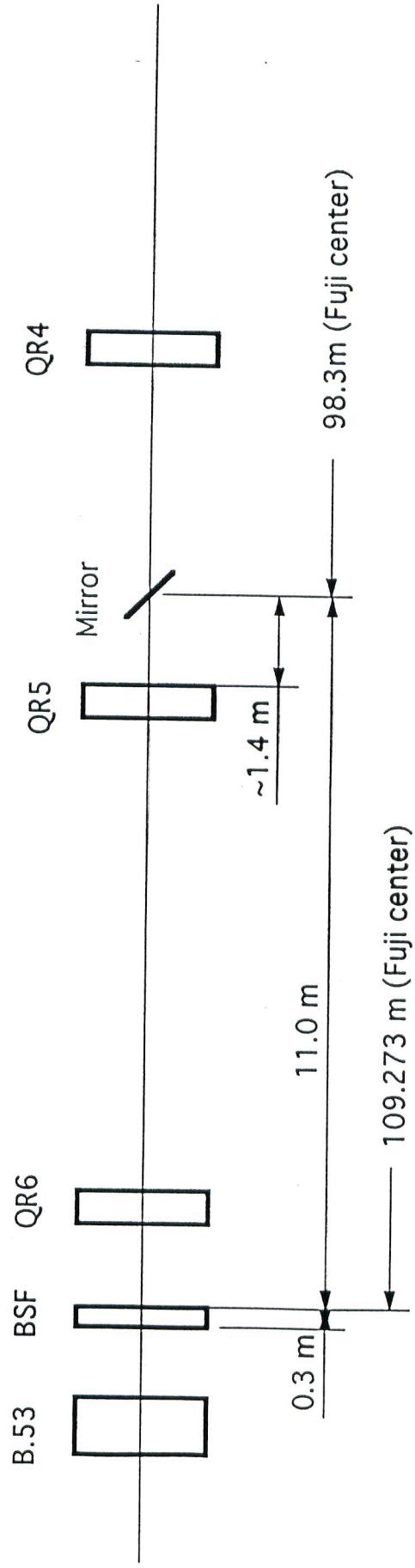
S/N ~ 92 dB

for 400ms processing
time (av. = 10).

(→ need factor 2)
reduction !



LER SOR Monitor (Fuji Straight Section)



BSF:

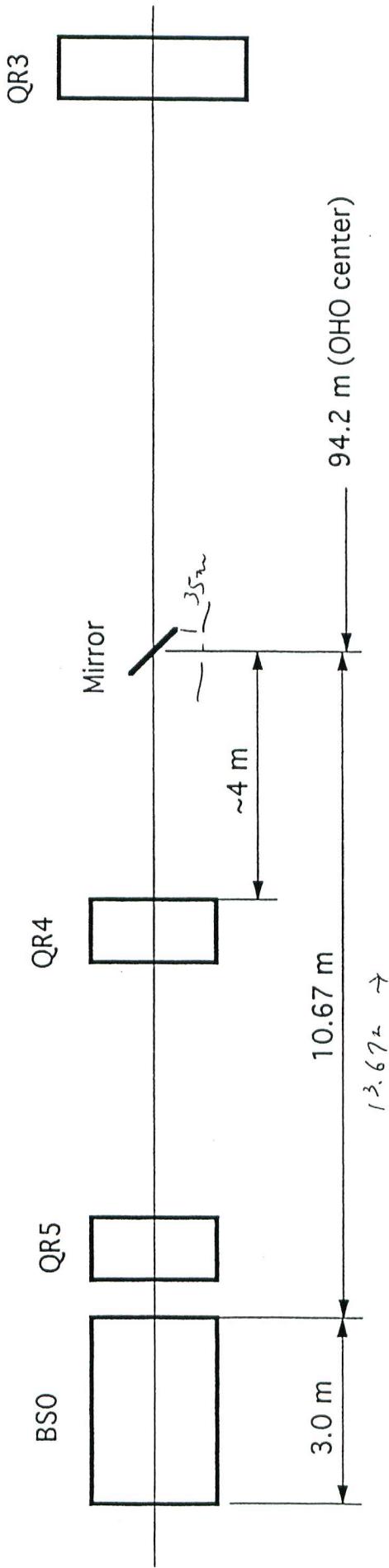
$\rho = 60$ m
 $\theta = 5$ mrad
 $P = 91.6$ W/mrad
@3.5 GeV, 2.6 A

Dec. 05, 1995 K. Satoh

LERSOR95Dec05.cad

HER SOR Monitor

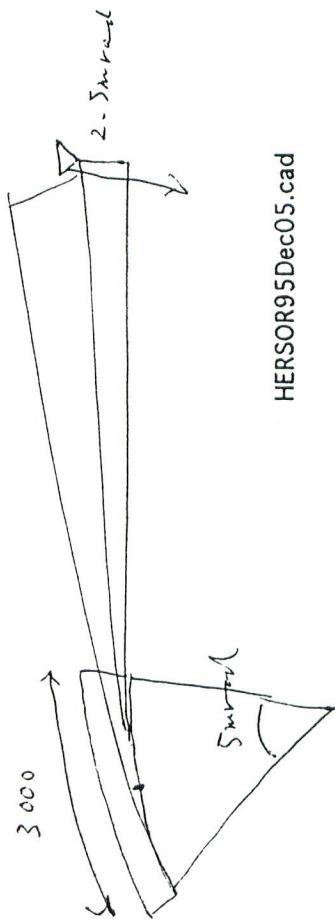
Oho Straight section



BSO:

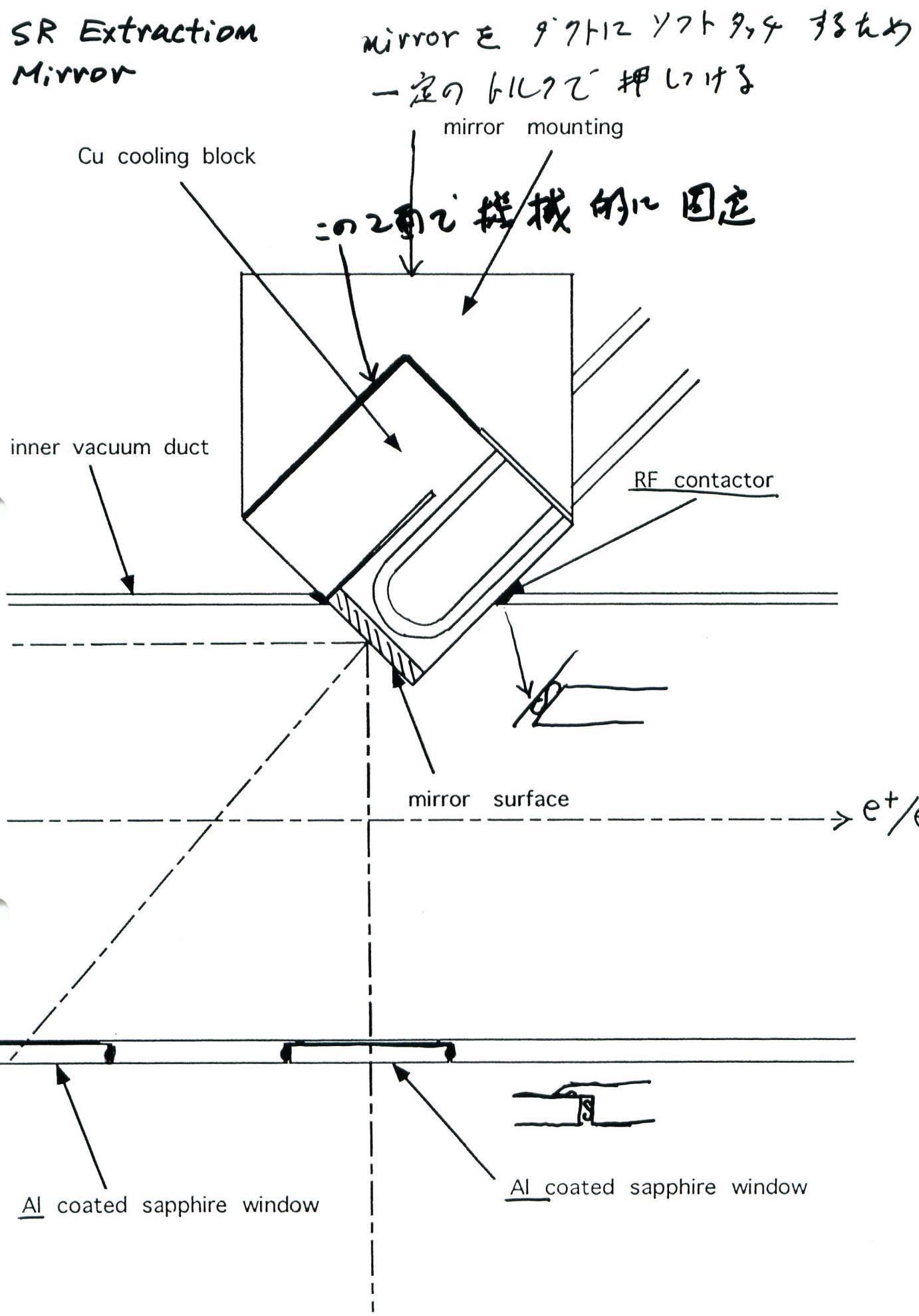
$$\begin{aligned} p &= 600 \text{ m} \\ \theta &= 5 \text{ mrad} \\ P &= 105.8 \text{ W/mrad} \\ @ 8 \text{ Gev}, 1.1 \text{ A} \end{aligned}$$

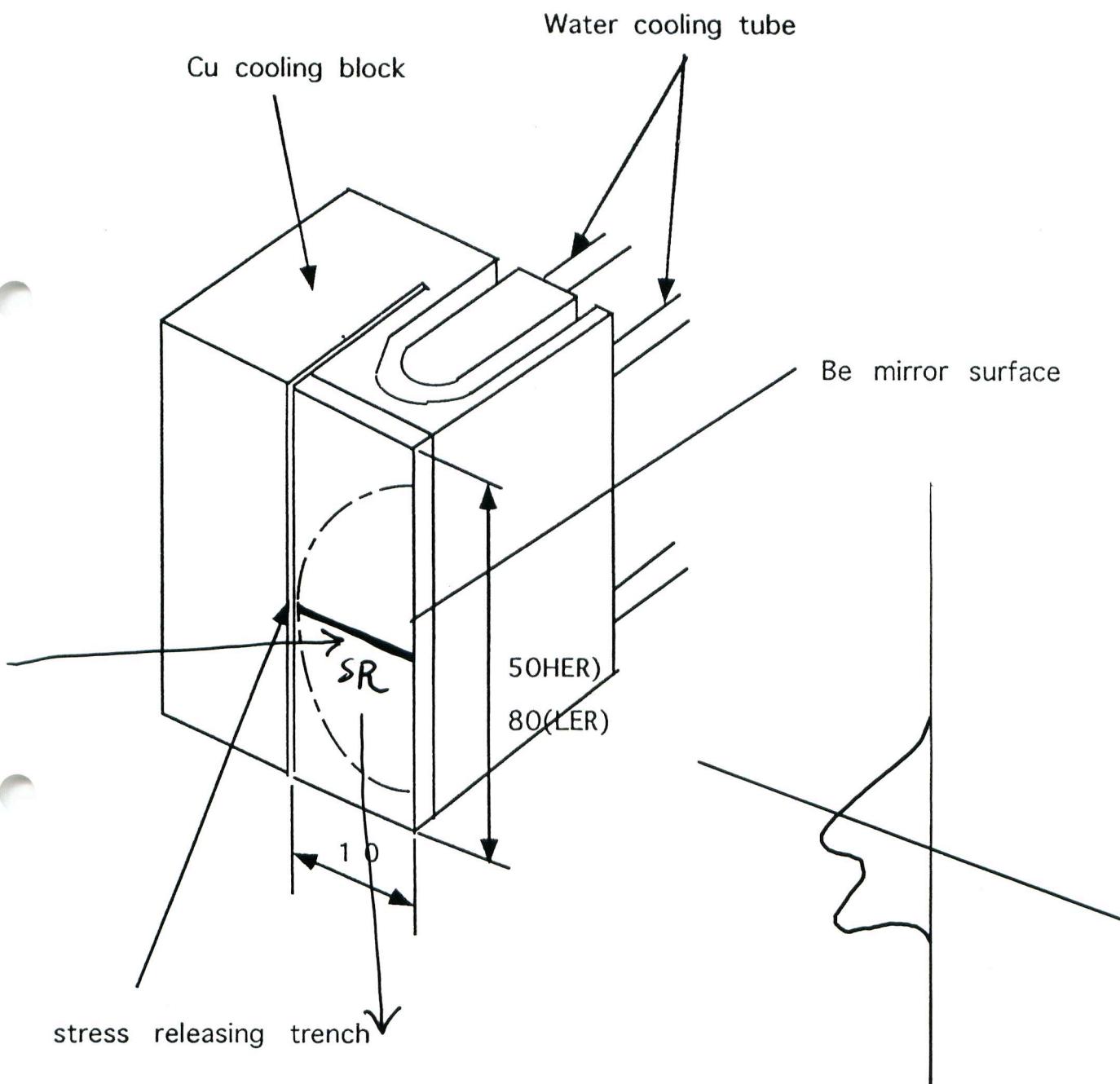
Dec05, 1995 K. Satoh



HERSOR95Dec05.cad

SR Extraction Mirror





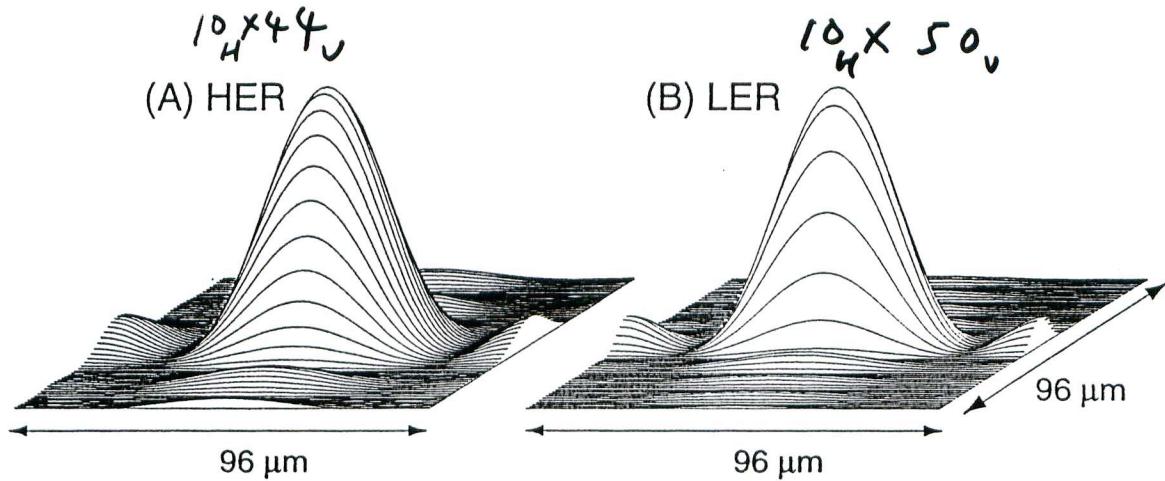


Figure 11.15: The Point Spread Function (PSF) of the focusing system. The side

	LER		HER	
	σ_x	σ_y	σ_x	σ_y
Original	472 μm	69 μm	650 μm	120 μm
With Aberration	472 μm	69 μm	650 μm	120 μm
With transverse diffraction	506 μm	102 μm	675 μm	158 μm
With longitudinal diffraction	422 μm	69 μm	655 μm	120 μm
Total	507 μm	102 μm	680 μm	158 μm

Table 11.2: Expected values of observed beam sizes which include contributions from effects of aberrations and diffraction.

11.3 Laser Wire Monitors

In addition to the beam profile monitor based on imaged synchrotron light, the use of so-called laser wires is under consideration for better resolution with an ability to measure individual bunches.

The principle of the measurement is illustrated in Figure 11.17. A narrow laser beam ("laserwire") meets a beam bunch perpendicularly, creating a number of Compton-scattered photons. The population of scattered photons is proportional to the overlap area of the laserwire and the particle beam. Therefore, by scanning the laser light horizontally or vertically, and by measuring the flux of Compton-scattered photons, one-dimensional particle distribution of the bunch is obtained.

Discussions in this section assumes that the laserwire is placed at the end of a straight section. However, since the laserwire technique can offer a very high resolution, it may be also used at the collision point. The practical application depends on the availability of an adequate room for measurement ports.

The accuracy of the measurement is determined by the ratio of the beam size to the laser

PF

deconvolution with PSF

beam, the beam profile was measured at the stored current of 1mA. The focus of the system was carefully adjusted at the balanced astigmatism point. A CCD TM7/4915 and image processor LBA100A of Spiricon company was used to observe the beam image.



Fig.4 A beam image of the Photon Factory. The ring energy is 1GeV and the beam current is 1mA.

The rms beam sizes from the beam image are 96.5 μm in the vertical and 280μm in the horizontal. The raw image of the beam as shown in Fig.4 is given by a convolution of the PSF (Fig.3) and the geometrical image. Considering the conjugation ratio of 0.148, the rms width of the PSF is almost same size as in the beam size. Therefore, to observe the original beam size, it is necessary to deconvolute the raw image by the PSF. Recently, deconvolution technique (restoration of the image) is currently used in the astronomical observation[3]. In the present time, a Wiener inverse filter [4] was applied. In the spatial frequency domain, the convolution integral is represented by

$$G(u,v)=H(u,v)F(u,v) + N(u,v) \quad (1)$$

where G denotes a two dimensional Fourier transform of blurred image, H is thought of as a inverse filter (two dimensional Fourier transform of PSF), F is a two dimensional Fourier transform of original image, and N is as a two dimensional Fourier transform of noise term in the image. The Wiener inverse filter H_w in equation (1) is given by

$$H_w(u,v) = \frac{H^*(u,v)}{|H(u,v)|^2 + \frac{\phi_n(u,v)}{\phi_f(u,v)}} \quad (2)$$

where the asterix indicates the complex conjugate of H. ϕ_n is the power spectra of the noise and ϕ_f is the power spectra of the signal. In the present time, the raw image was taken at the balances astigmatism point, we neglect asymmetric components of the obtained PSF as shown in Fig.3, and use a Gaussian approximation as the PSF. To perform the deconvolution process, we use the computer code Hidden Image which has the maximum entropy deconvolution method. A result of the deconvolution is shown in Fig.5. The rms beam sizes from this beam profile are 49.2 μm in the vertical and 206μm in the horizontal. By the use of measured values of β function, The emittance at 1GeV operation of the ring are 0.13 nmrad in the vertical and 22 nmrad in the horizontal.



Fig. 5 Beam profile after deconvolution process, scale is same as in Fig.4.

6 CONCLUSIONS

A beam profile monitor for the high brilliant configuration of the Photon Factory was designed and constructed. A Be-mirror was applied as a extraction mirror of The visible SR beam. We have analyzed aberration of the focusing system including the deformation of the Be-mirror in the Fourier optical manner, and obtained a PSF at balanced astigmatism point. We measured a beam profile of the Photon Factory with a ring energy of 1GeV at the balanced astigmatism point of the focusing system. By the use of obtained PSF and beam profile image, we applied the image restoration method. After the image restoration process, we obtained a beam emittances 0.13 nmrad in the vertical and 22 nmrad in the horizontal. We conclude; 1. the present system has a enough performance to measure the small emittance in the high brilliant configuration of the Photon Factory; 2. the image restoration technique with measured PSF as used in the astronomical observation is very useful tool not only to eliminate the aberration of the focusing system but also obtaining the geometrical image.

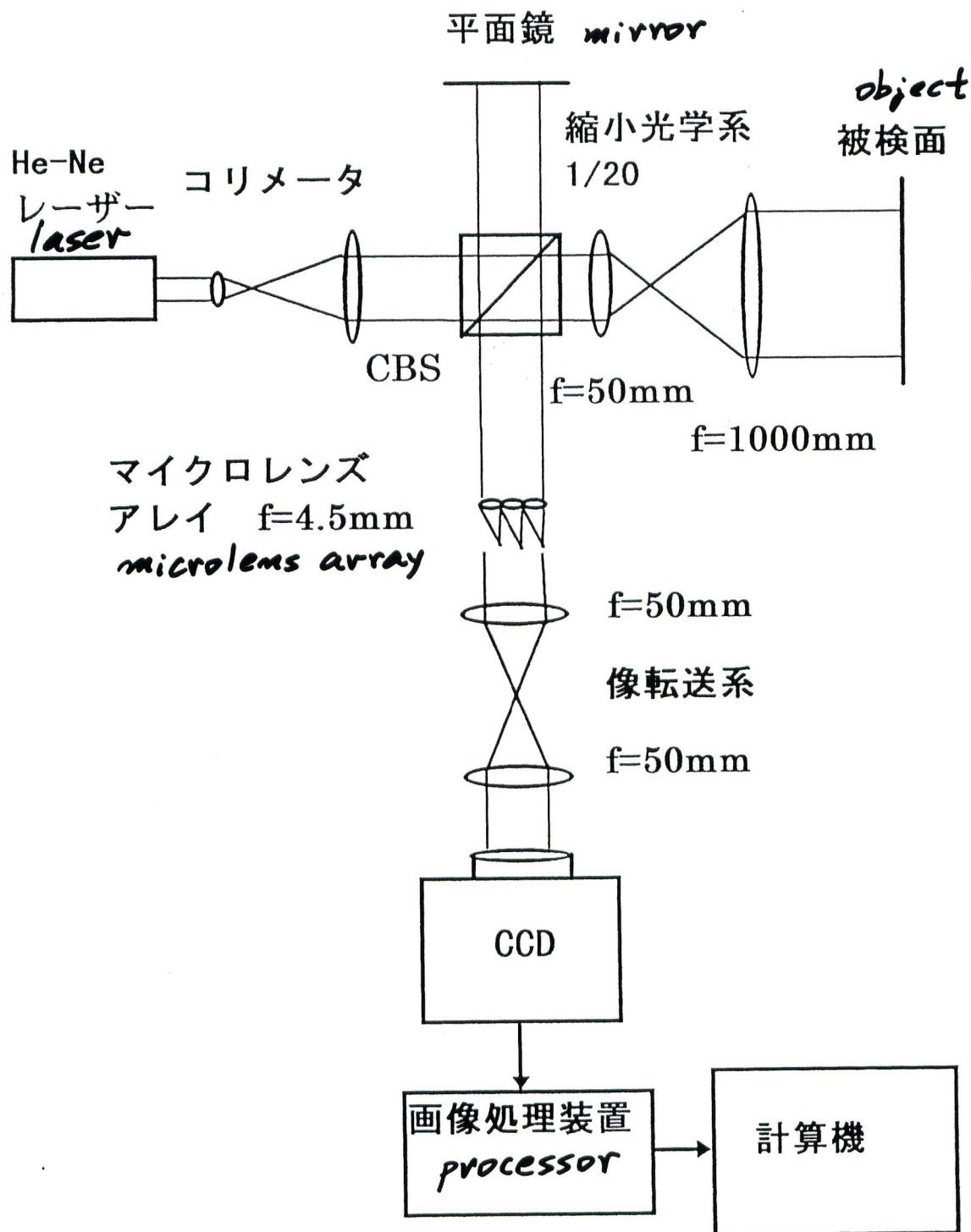
7 ACKNOWLEDGMENTS

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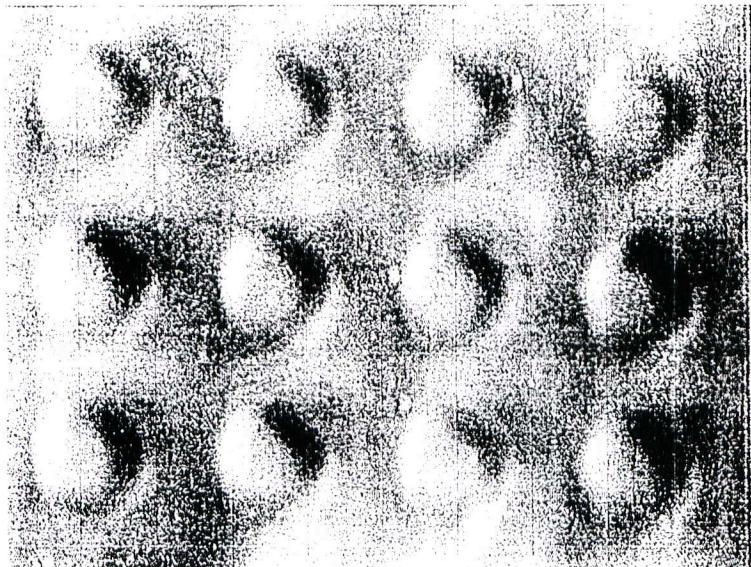
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- [2] M.Born and E. Wolf,"Principles of Optics, P459 Pergamon press. (1980).
- [3] N.Weir,"Applications of Maximum Entropy Techniques to HST Data", Proc. the ESO/STECF Data analysis work shop, (1991).
- [4] A.Rosenfeld and A.C.Kak,"Digital Picture Processing", Academic Press, Inc. (1976).

Shack Hartmann センサー

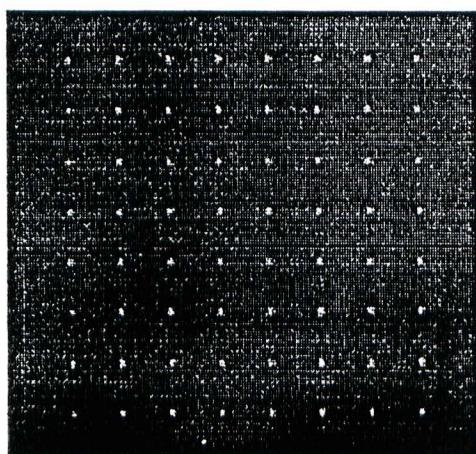


microlens array
マルチレンズアレイ



焦点距離	4.5mm	<i>f</i>
レンズ径	$150\mu\text{m}$	<i>lens diam.</i>
ピッチ	$250\mu\text{m}$	<i>lens pitch</i>
素子数	8×8	<i># of lens</i>

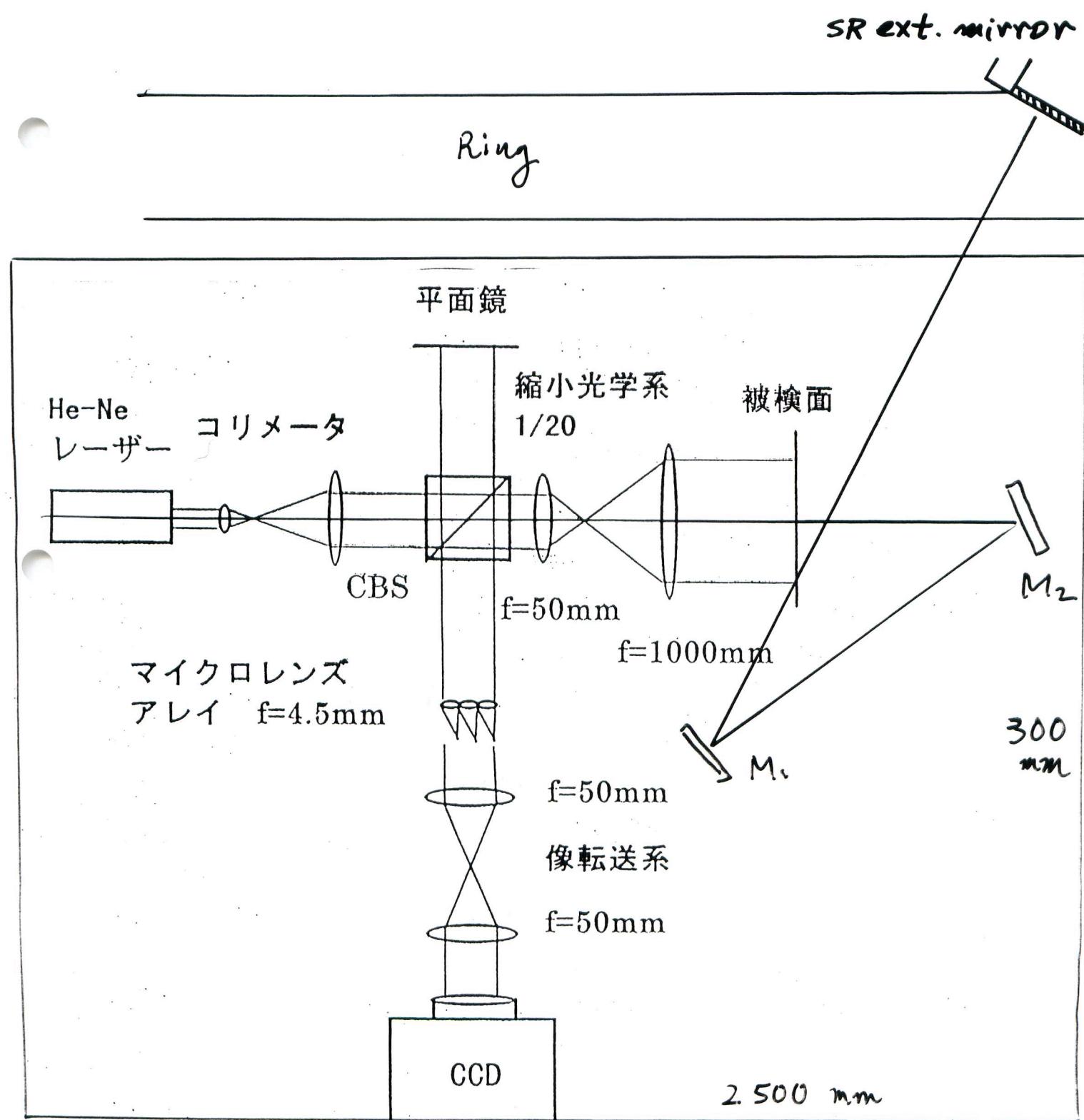
spot-pattern
マルチレンズアレイの集光パターン



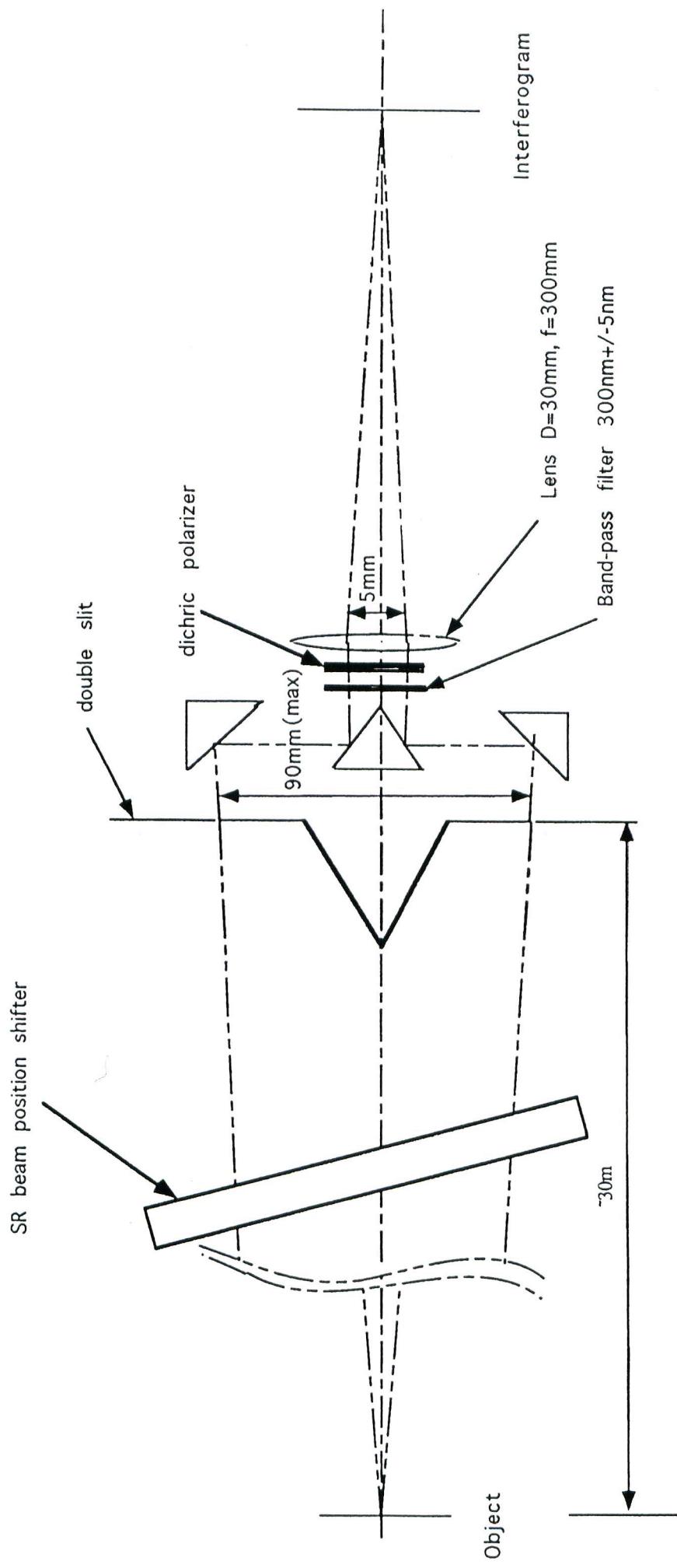
スポット径 $30\mu\text{m}$ *spot*

Shack - Hartmann シャック・ハルトマンの 配置

Configuration of the Shack-Hartmann Sensor
in the Ring

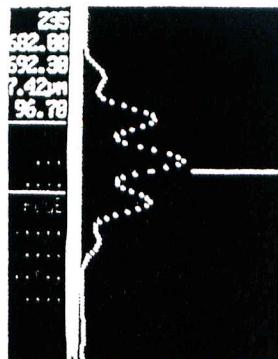


Beam size measurement 偏光干涉計

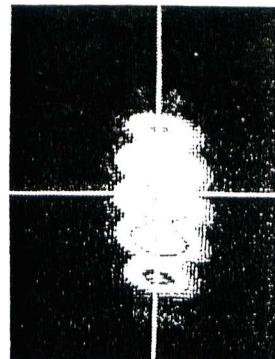


Two beam interferometer for B factory

PF 2°
の空気



6 nm 700 nm 11

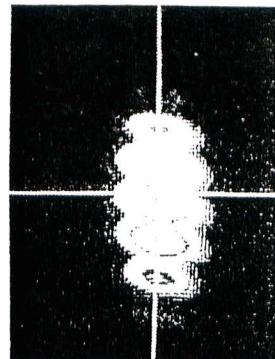
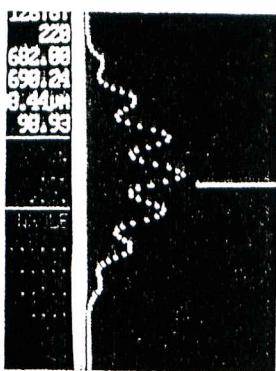


Double-slit
interferometer at PF

$$D = 6 \text{ mm}$$

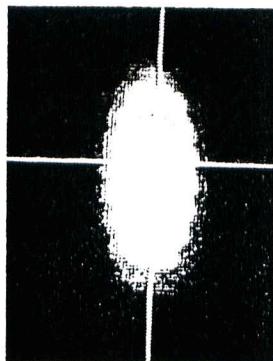
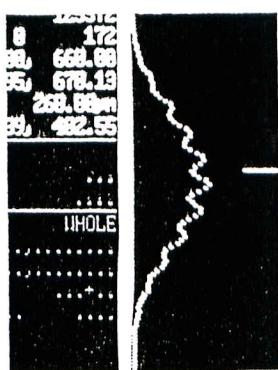
$$\lambda = 700 \text{ nm}$$

$$\Delta\lambda = 10 \text{ nm}$$

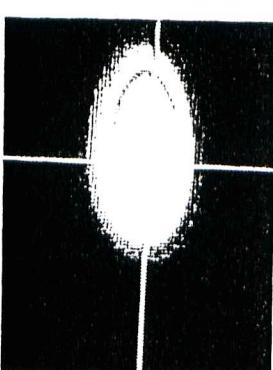
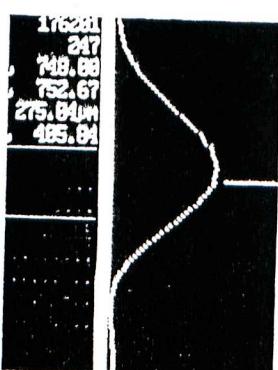


$$D = 7 \text{ mm}$$

6



$$D = 10 \text{ mm}$$



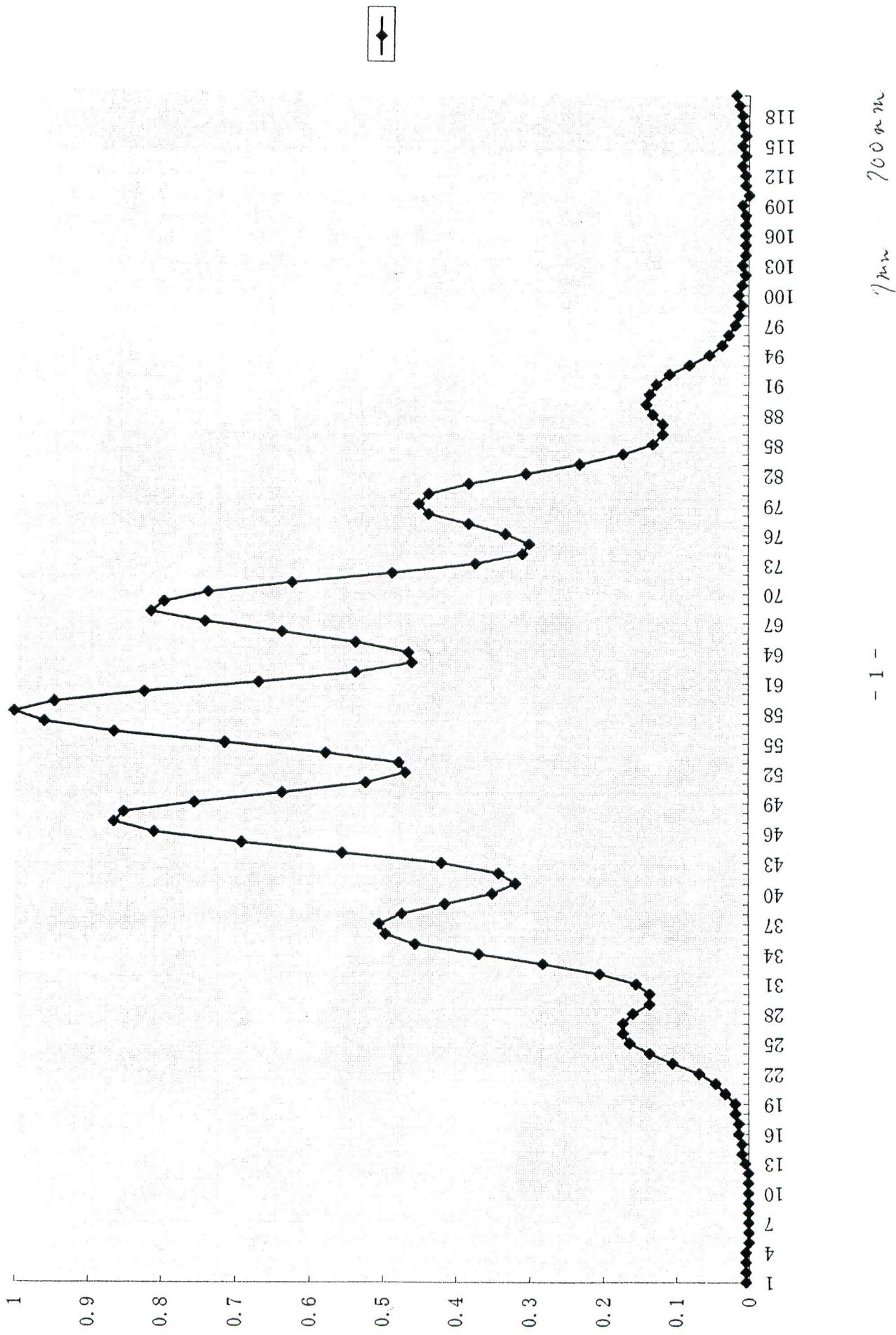
$$D = 15 \text{ mm}$$

$$\rightarrow \sigma = 170 \mu\text{m}$$

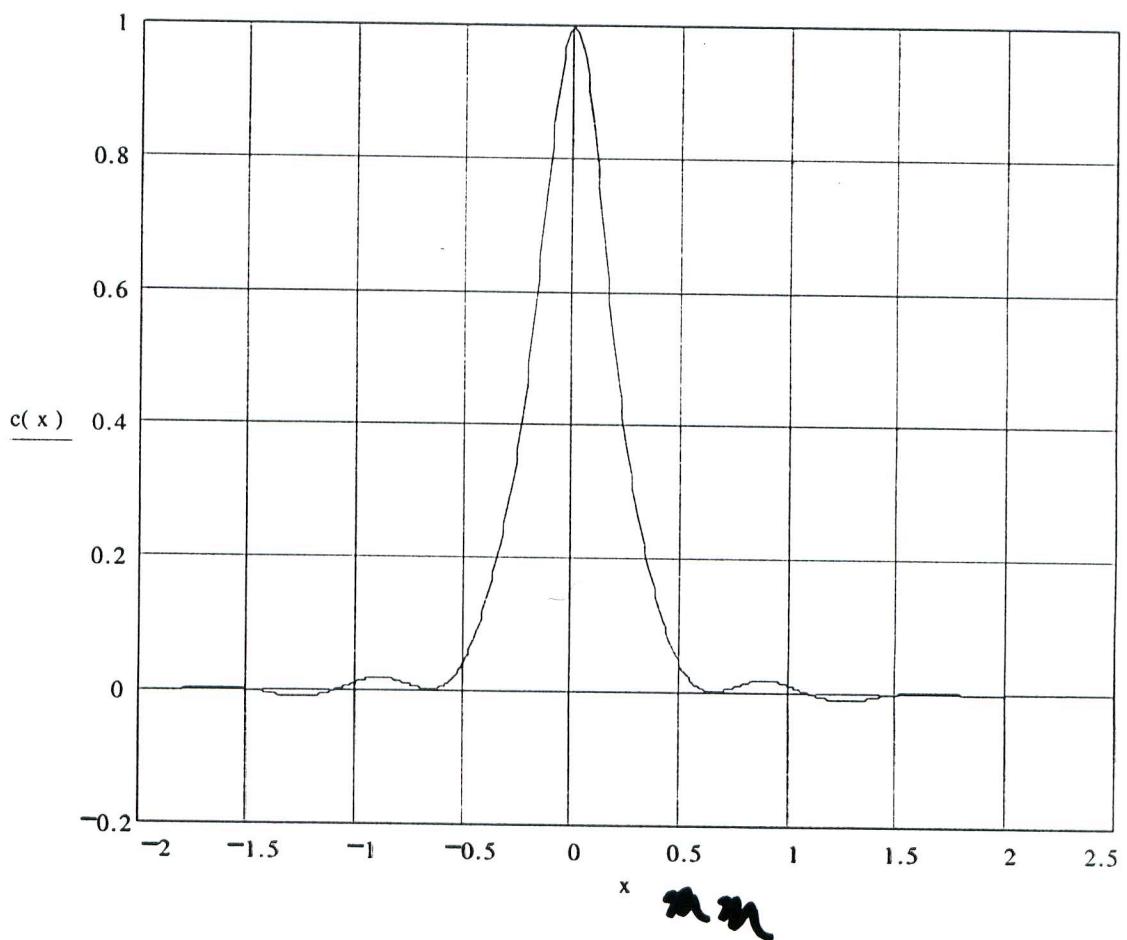
15 mm 700 nm 10.7

Interferogram

INTER12 グラフ 3



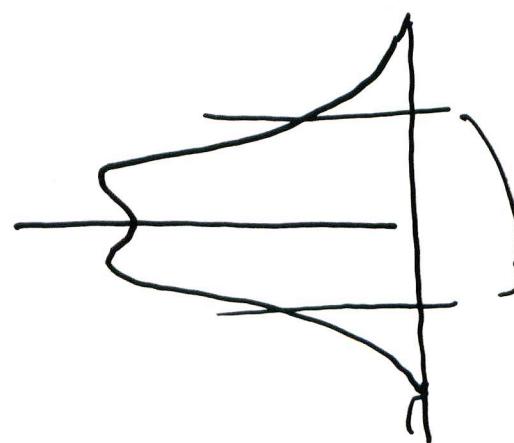
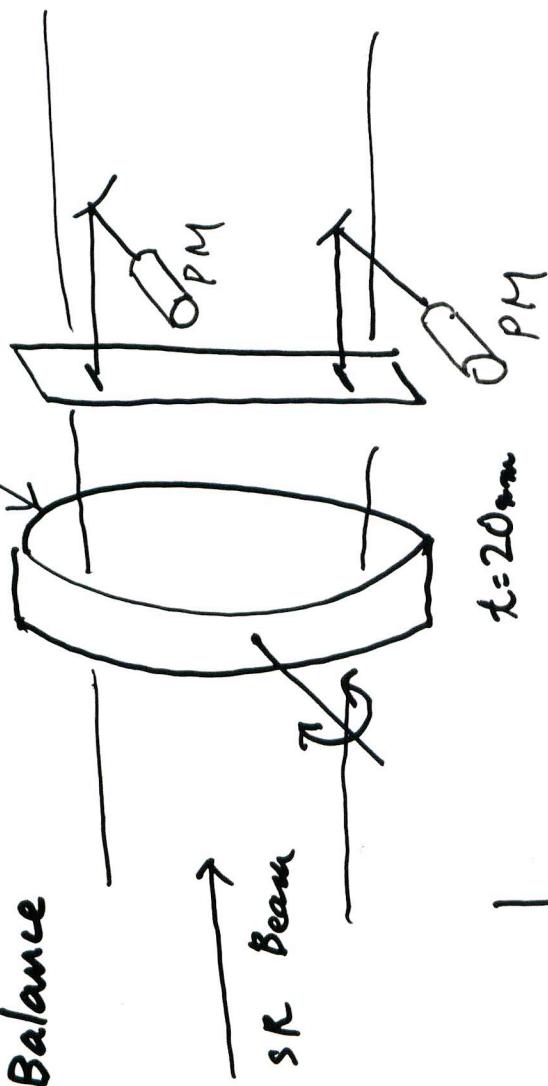
Reconstructed Beam Profile



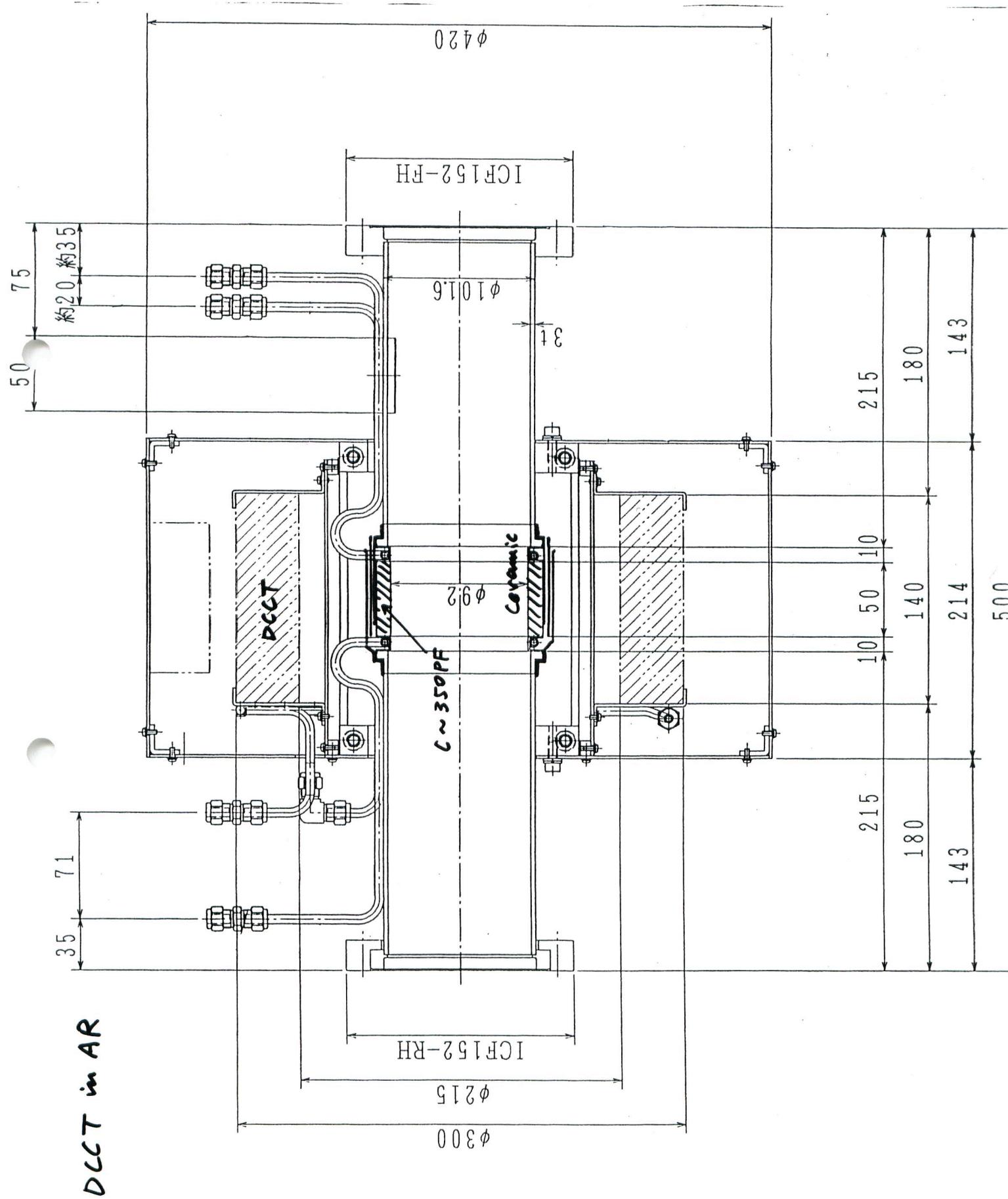
7-12 重建 no 2 手写 C-a 7.03.16

$$\sigma = 170 \mu\text{m} (60\%)$$

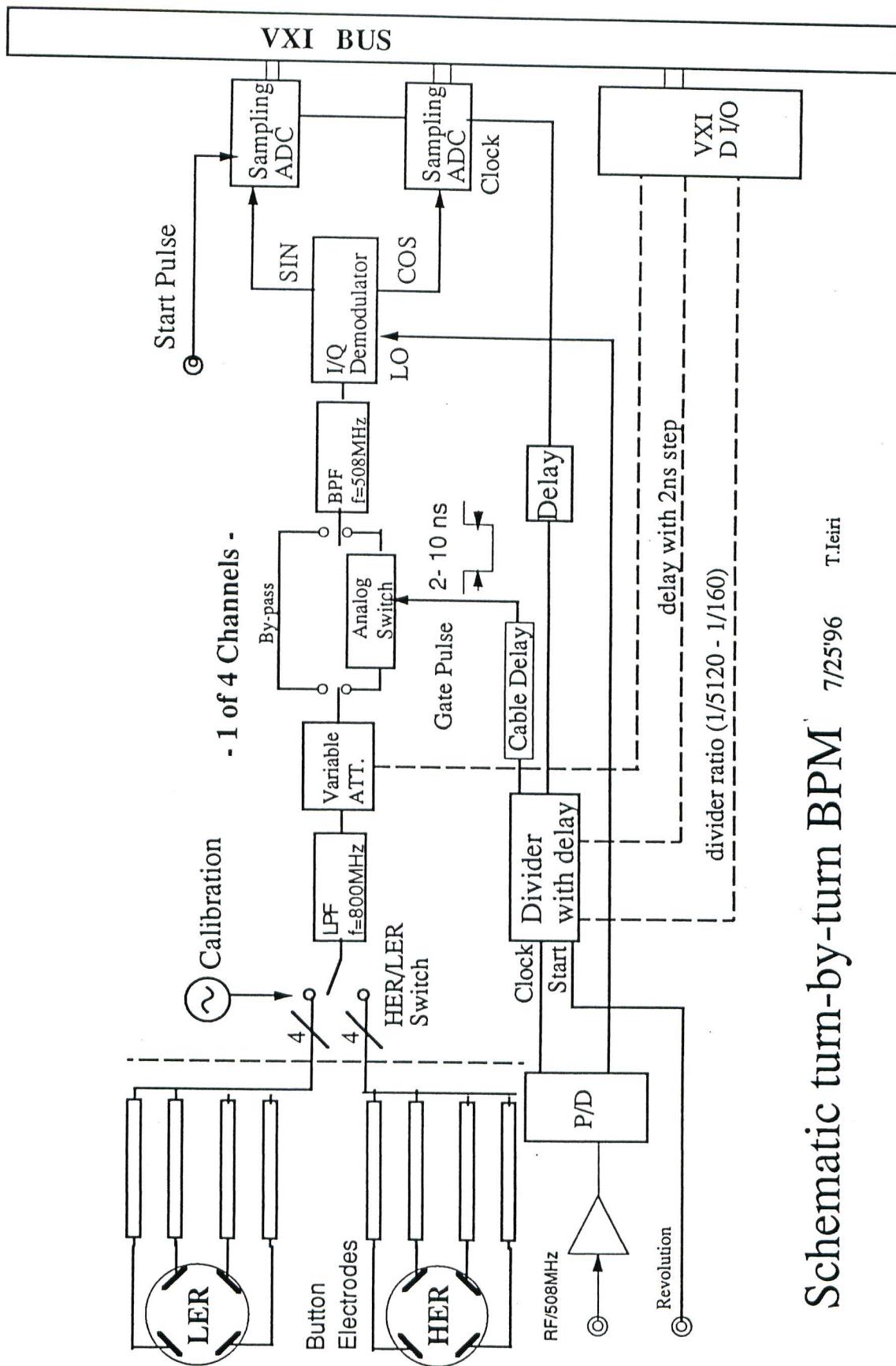
L-4 - 77 -
Beam Shifter for
Intensity Balance



L-4 - 77 -
Beam Shifter for
Intensity Balance
Graph of Intensity vs Position



Schematic turn-by-turn BPM 7/25'96 T.Ileiri



BELLE Detector

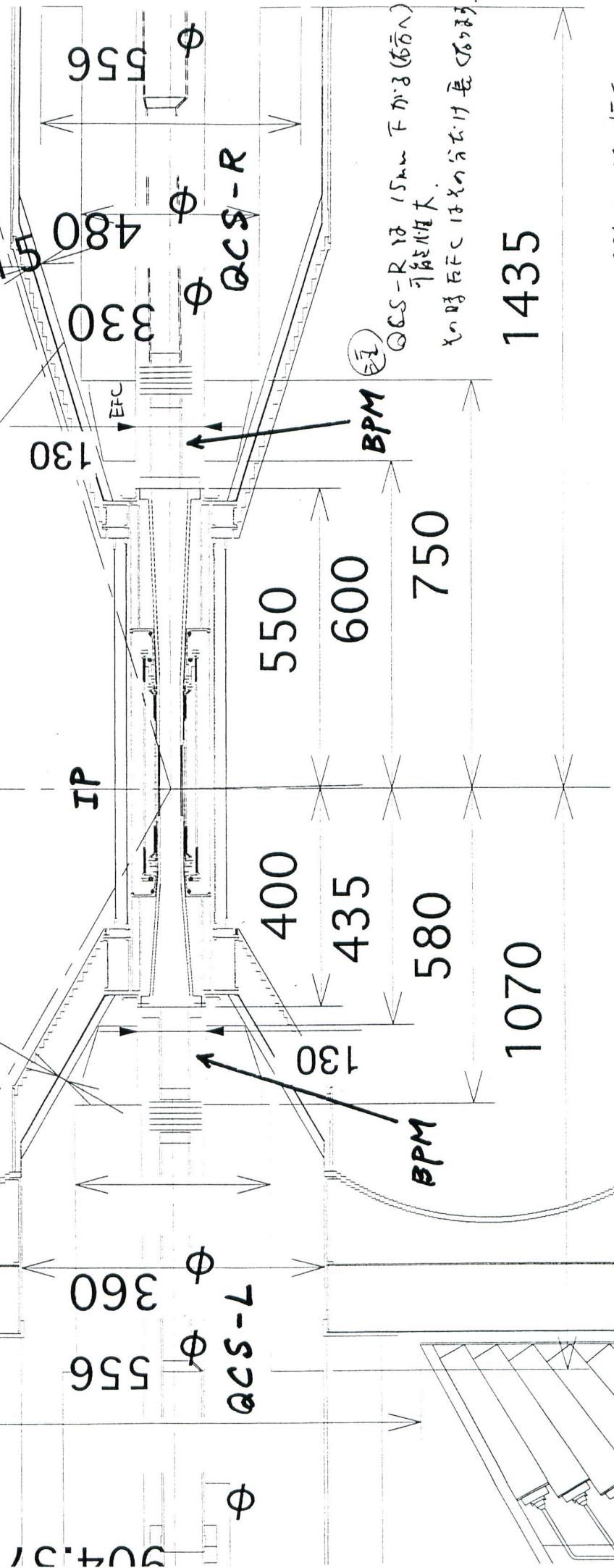
1670

SVD Data Scanner

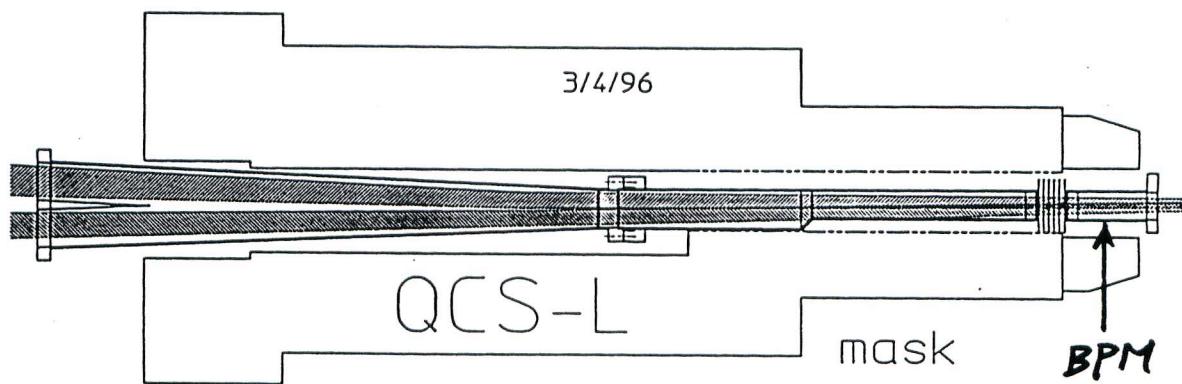
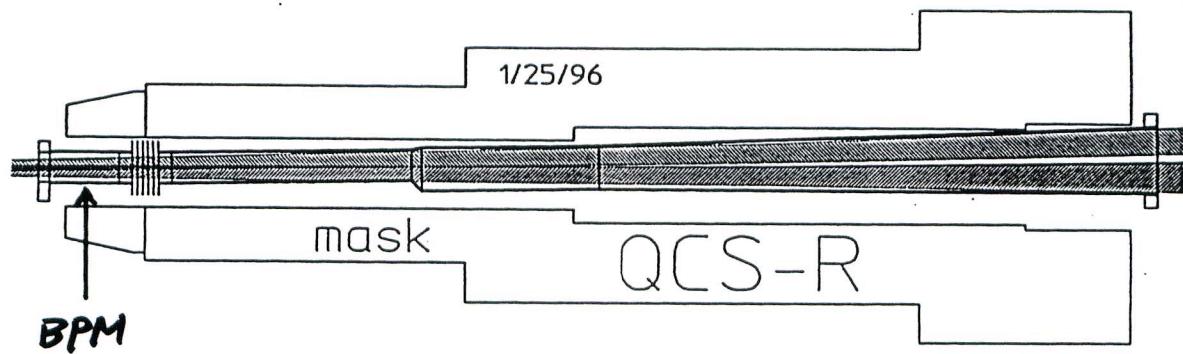
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1650

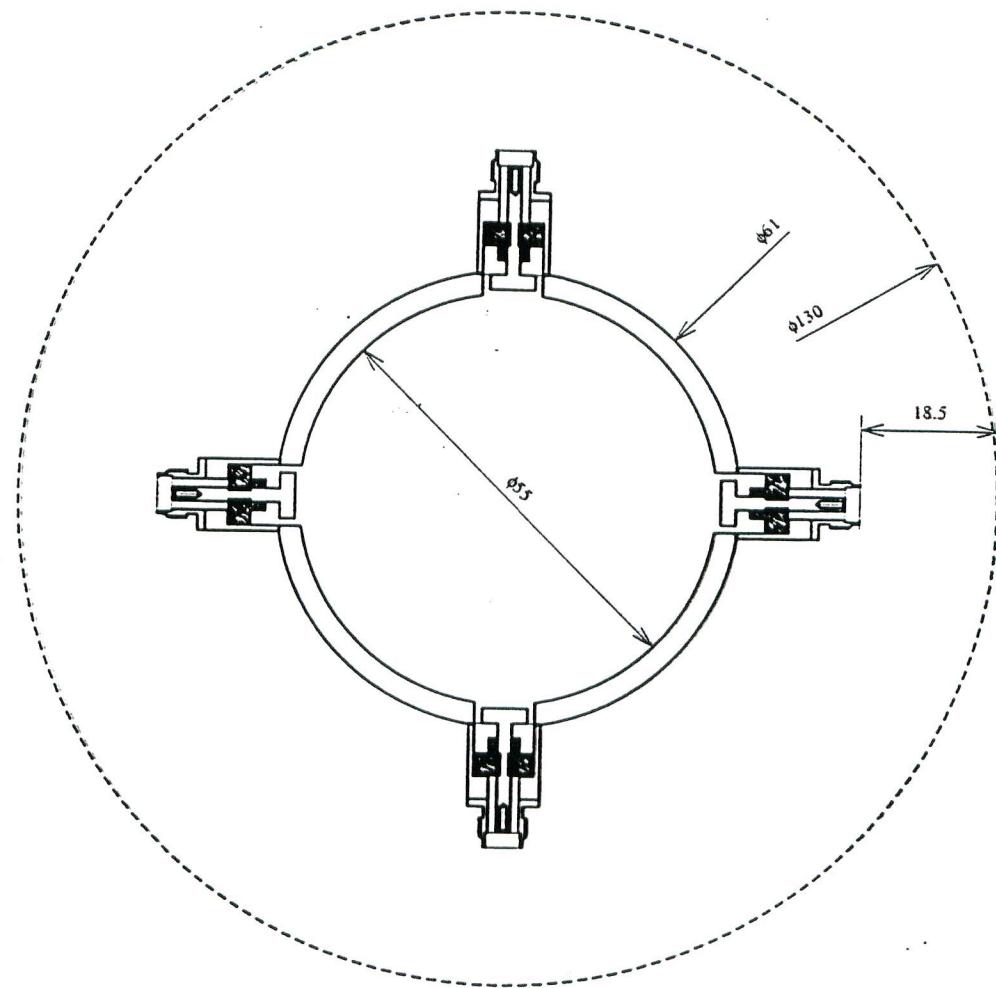
ケーブル領域



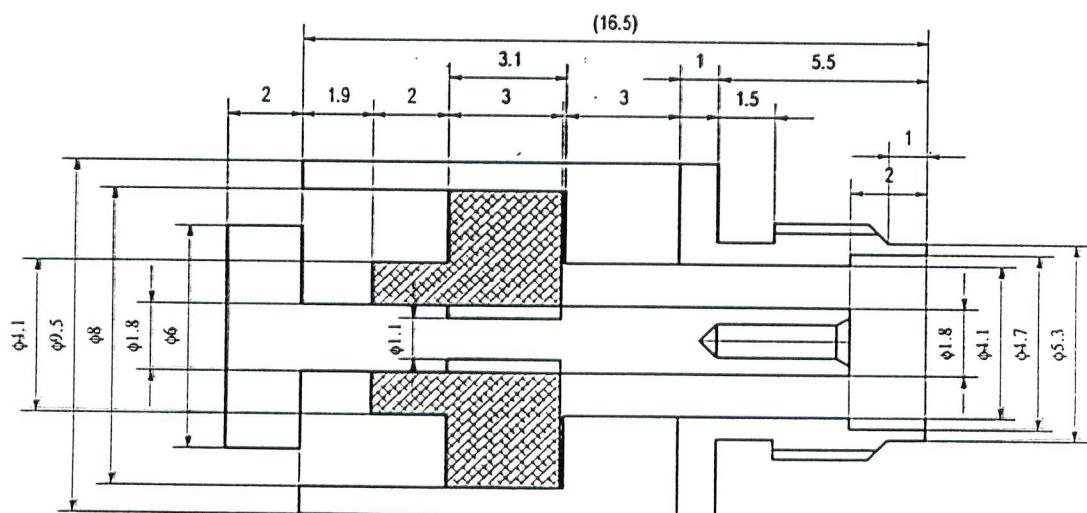
1996.12.19 横浜 (-334)



BPM at IR

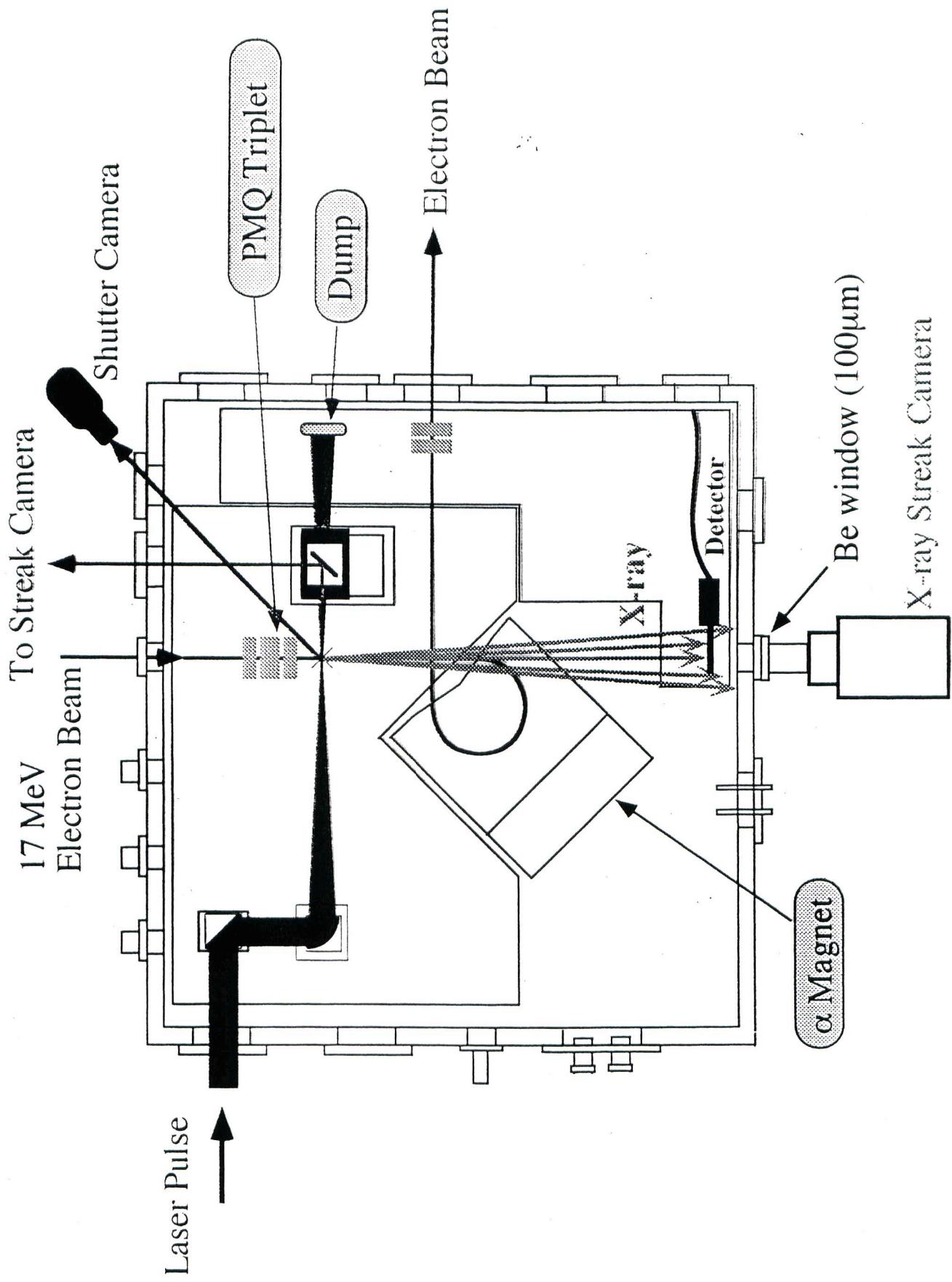


Feedthrough



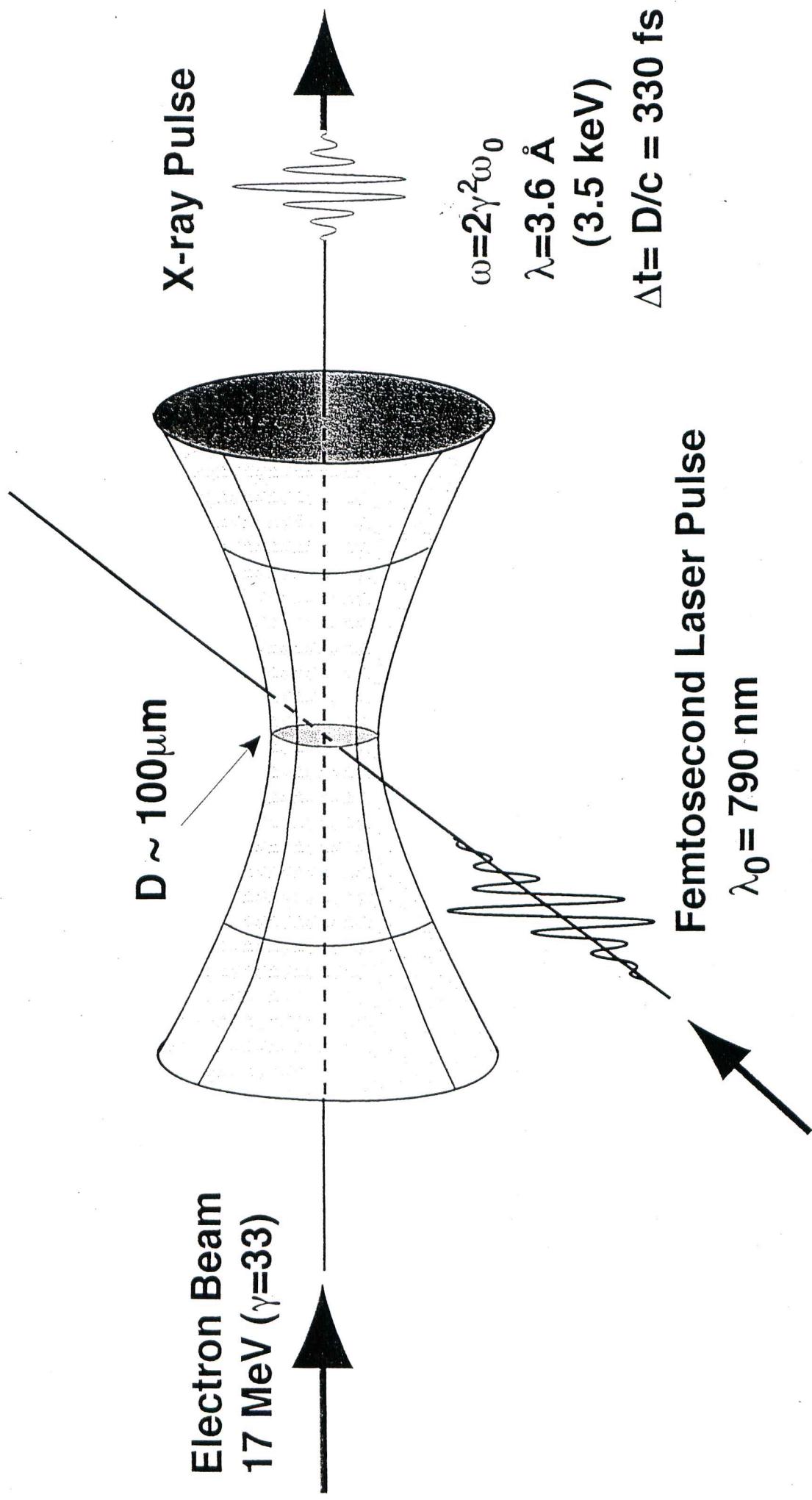
(SMA)

Thomson Scattering Experimental Setup

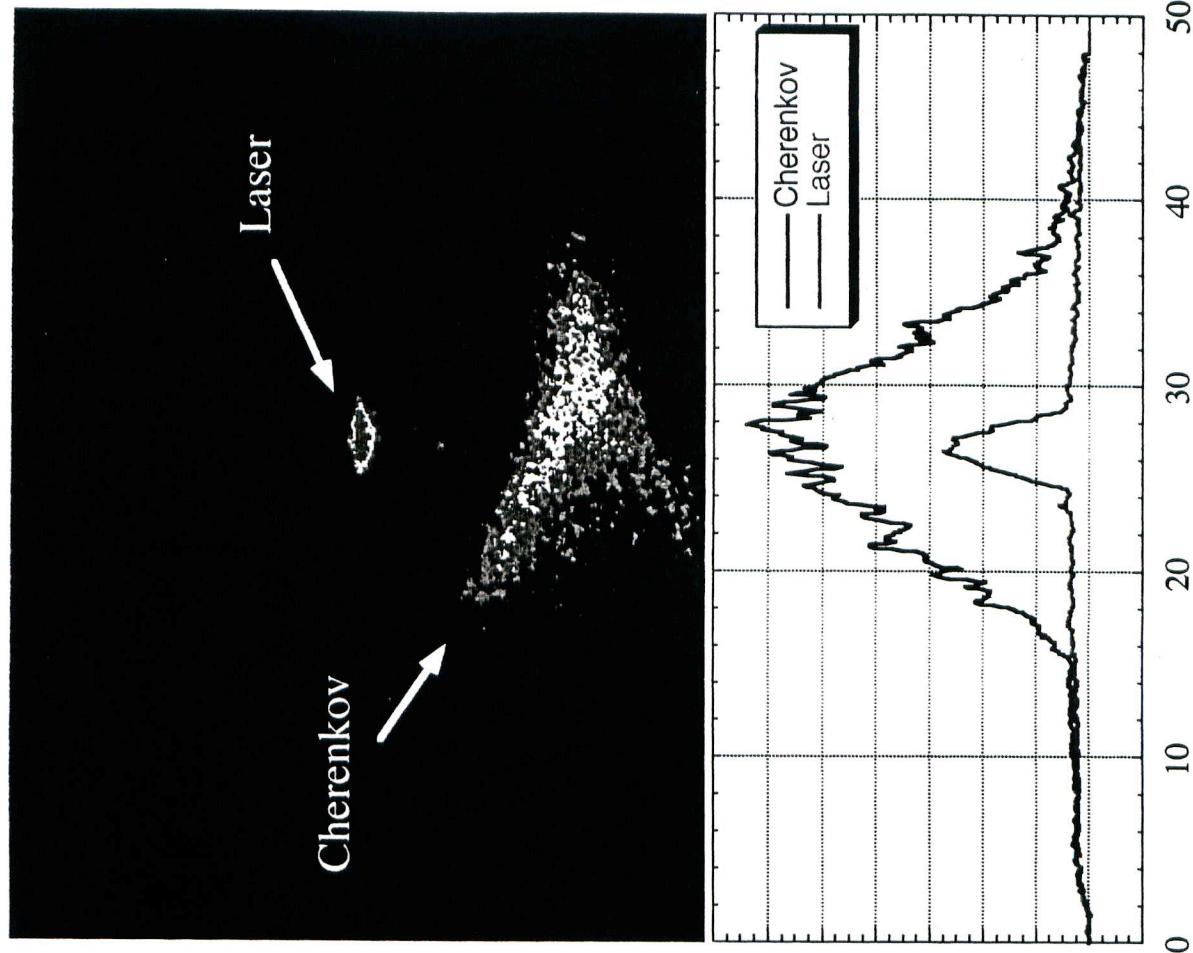


Subpicosecond X-ray Generation by Thomson Scattering

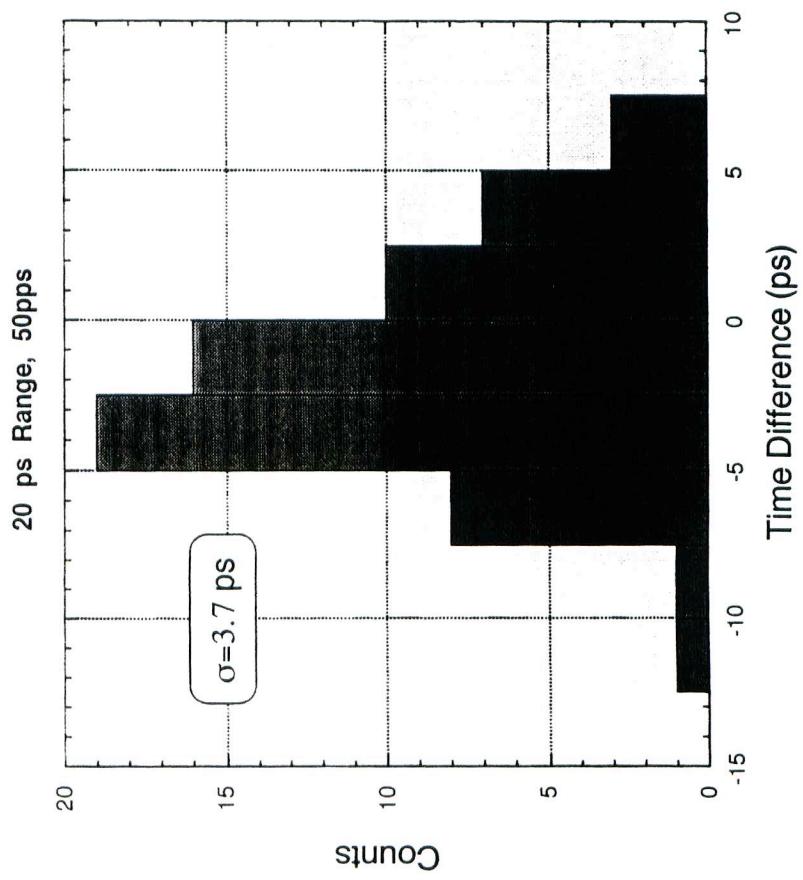
K. J. Kim et al., Nucl. Instr. and Meth., A341 (1994) 351-354



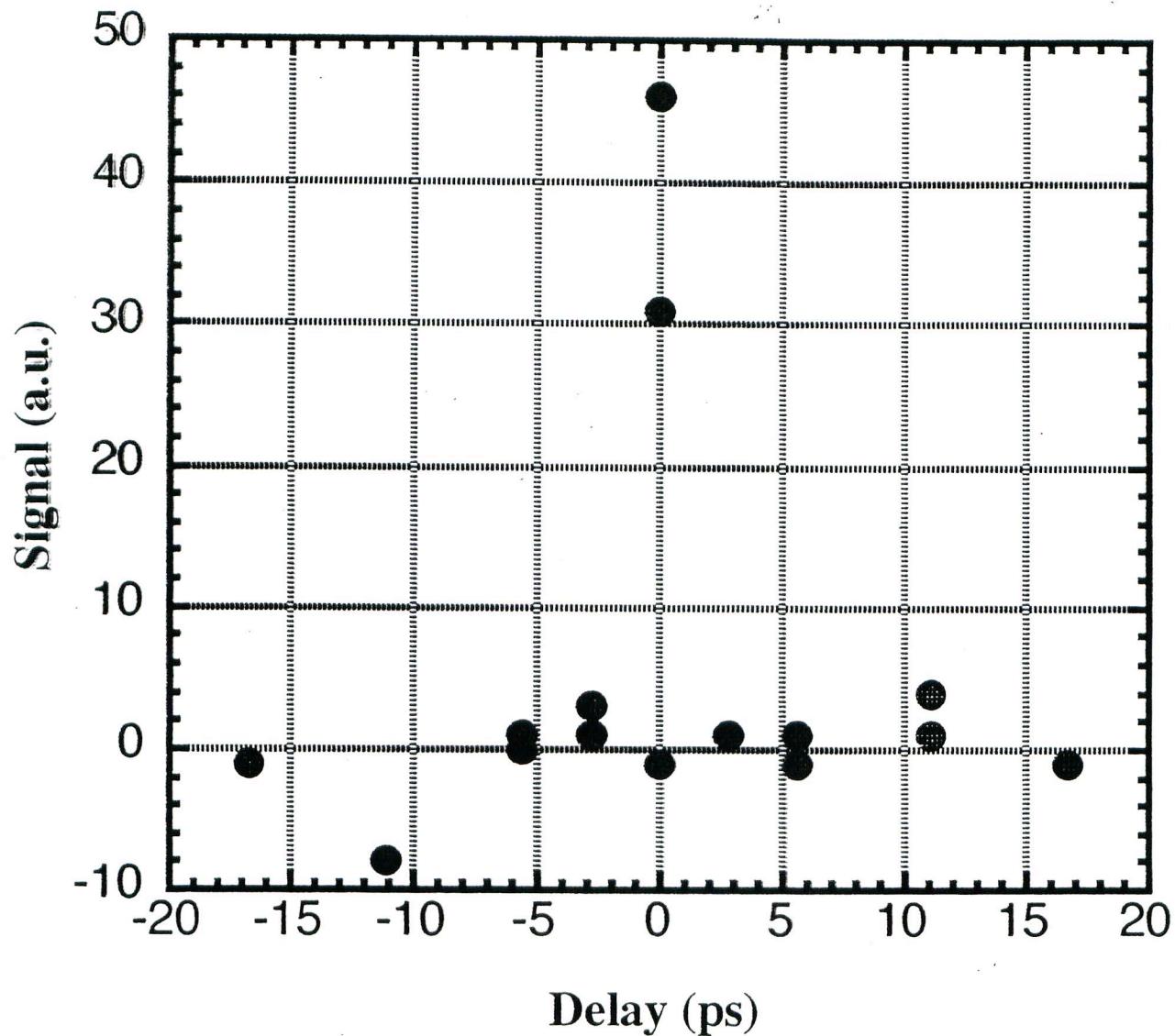
Synchrotron Image of Synchronized Cherenkov Light and Laser



Measurement of Timing Jitter between Laser and Electron



X-ray Signal from Thomson Scattering



Test of Bunch Current Monitor in AR

